

# R&D for ATLAS planar pixels for HL-LHC

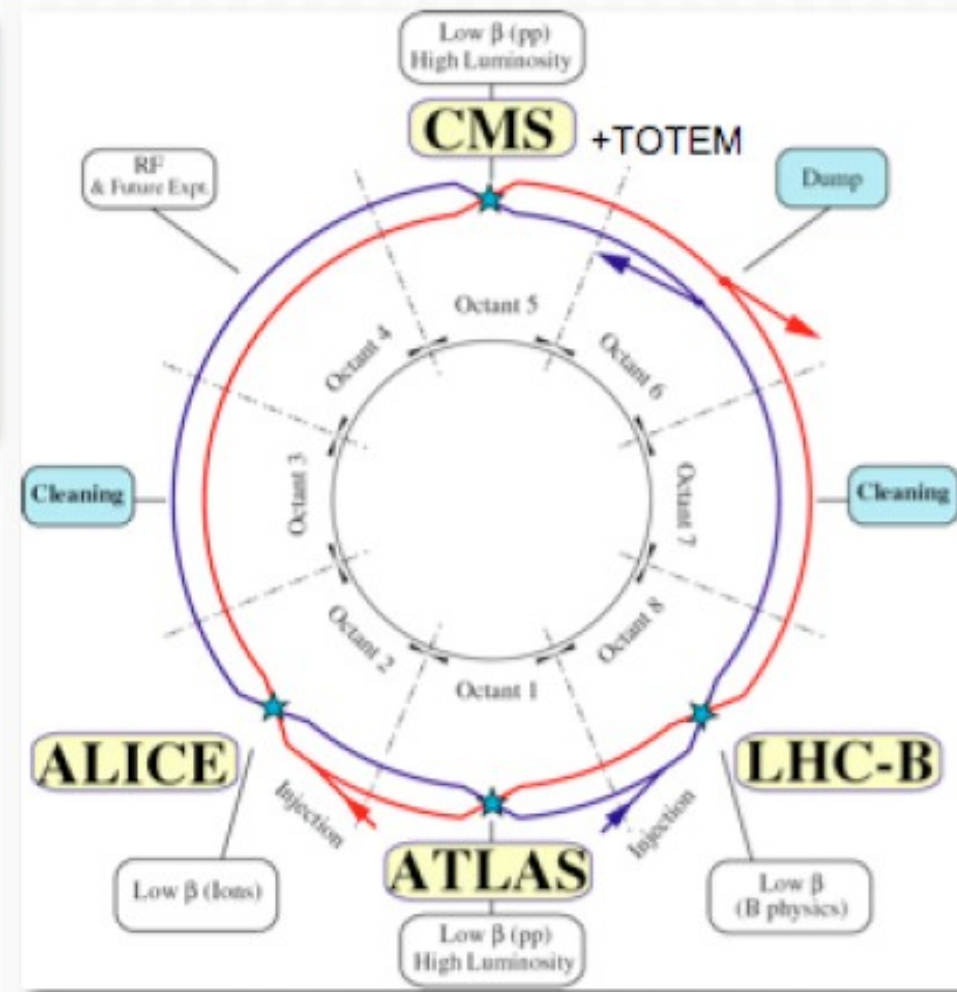
*Marco Bomben - LPNHE*

- Introduction
- The LHC upgrade
- The ATLAS upgrade
- The R&D for a new Inner Detector: the ATLAS Upgrade Planar Pixel Sensor
- Conclusions

# INTRODUCTION



- 1232 superconducting dipoles
  - 15m long at 1.9 K,  $B=8.33$  T
  - Inner coil diameter = 56 mm
- beam-energy 7 TeV (7x TEVATRON)
- Luminosity  $10^{34} \text{ cm}^{-2}\text{s}^{-1}$  (>100x TEVATRON)
- Bunch spacing 24.95 ns
- Particles/bunch  $1.1 \cdot 10^{11}$
- Stored E/beam 350 MJ  $\sim$  80kg of TNT
- Also : Lead Ions operation
  - Energy/nucleon 2.76 TeV / u
  - Total initial lumi  $10^{27} \text{ cm}^{-2} \text{ s}^{-1}$

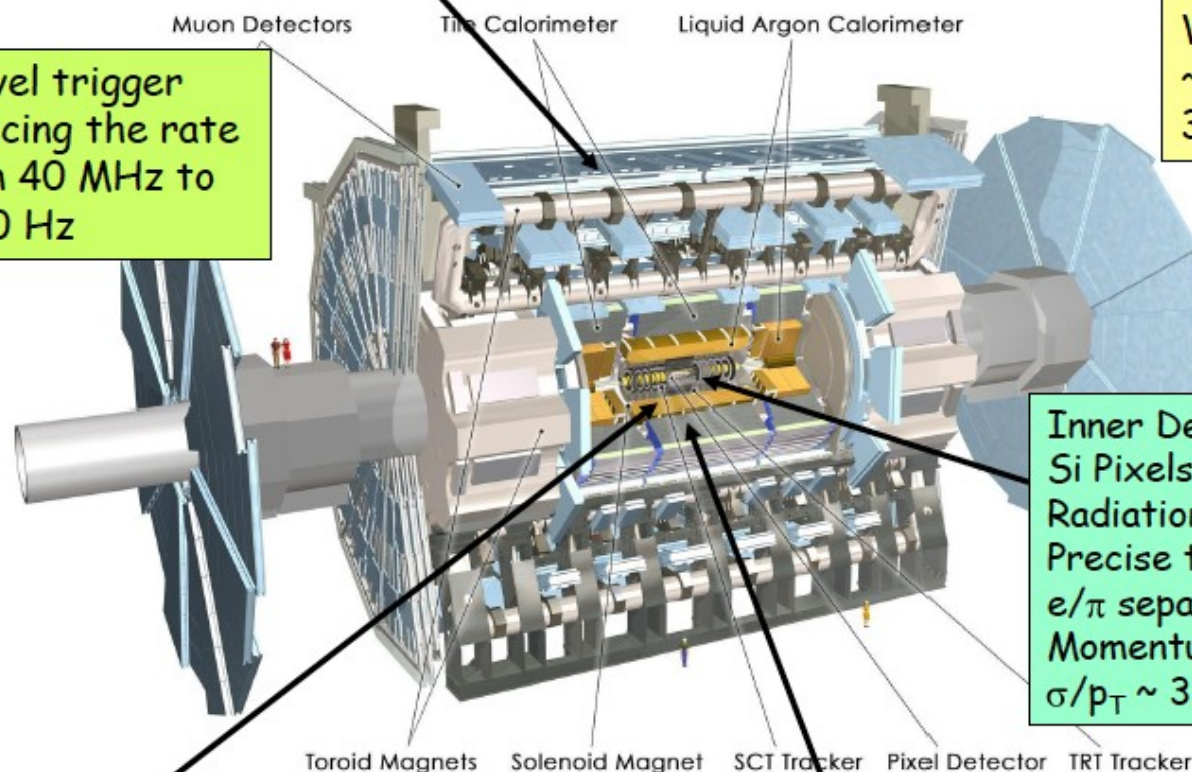


- 8 independent sectors
  - Challenge for control, powering
- 10 GJ stored in magnets
- Warm insertion regions for beam dump, cleaning, acceleration

Muon Spectrometer ( $|\eta| < 2.7$ ) : air-core toroids with gas-based muon chambers  
Muons trigger and measurement with momentum resolution  $< 10\%$  up to  $E_\mu \sim 1 \text{ TeV}$

Length :  $\sim 46 \text{ m}$   
Radius :  $\sim 12 \text{ m}$   
Weight :  $\sim 7000 \text{ tons}$   
 $\sim 10^8$  electronic channels  
3000 km of cables

3-level trigger  
reducing the rate  
from 40 MHz to  
 $\sim 200 \text{ Hz}$

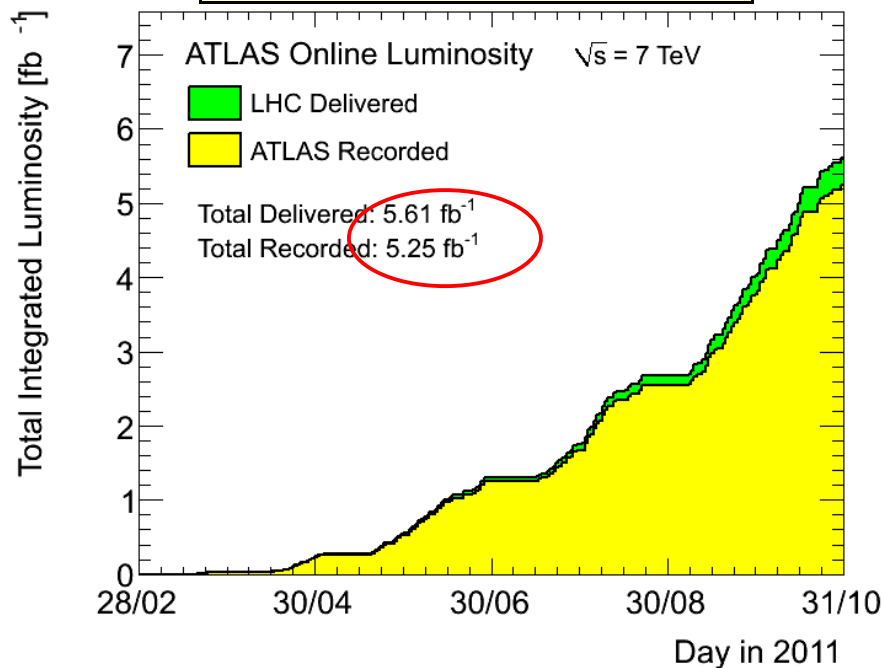


Inner Detector ( $|\eta| < 2.5$ ,  $B=2\text{T}$ ):  
Si Pixels, Si strips, Transition  
Radiation detector (straws)  
Precise tracking and vertexing,  
 $e/\pi$  separation  
Momentum resolution:  
 $\sigma/p_T \sim 3.8 \times 10^{-4} p_T (\text{GeV}) \oplus 0.015$

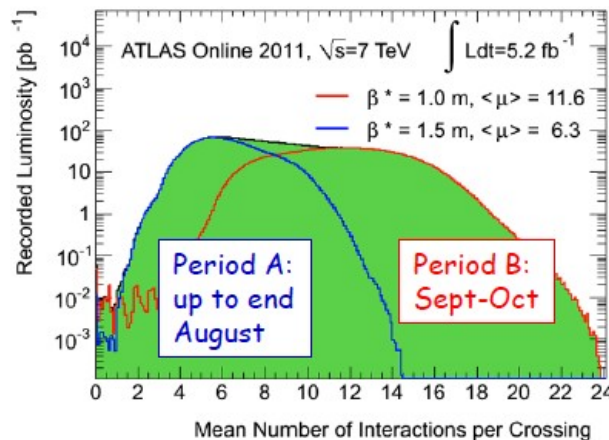
EM calorimeter: Pb-LAr Accordion  
 $e/\gamma$  trigger, identification and measurement  
E-resolution:  $\sigma/E \sim 10\%/\sqrt{E}$

HAD calorimetry ( $|\eta| < 5$ ): segmentation, hermeticity  
Fe/scintillator Tiles (central), Cu/W-LAr (fwd)  
Trigger and measurement of jets and missing  $E_T$   
E-resolution:  $\sigma/E \sim 50\%/\sqrt{E} \oplus 0.03$

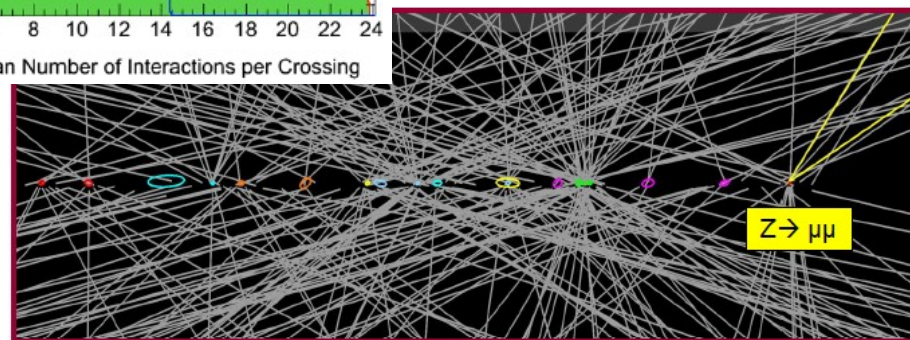
Peak luminosity  
seen by ATLAS:  
 $\sim 3.6 \times 10^{33} \text{ cm}^{-2} \text{ s}^{-1}$



Price to pay for the high luminosity:  
larger-than-expected pile-up



Event with 20  
reconstructed vertices  
(ellipses have  $20 \sigma$  size for  
visibility reasons)



Fraction of non-operational detector channels:  
(depends on the sub-detector)

few permil to 3.5%

Data-taking efficiency = (recorded lumi)/(delivered lumi):

$\sim 93.5\%$

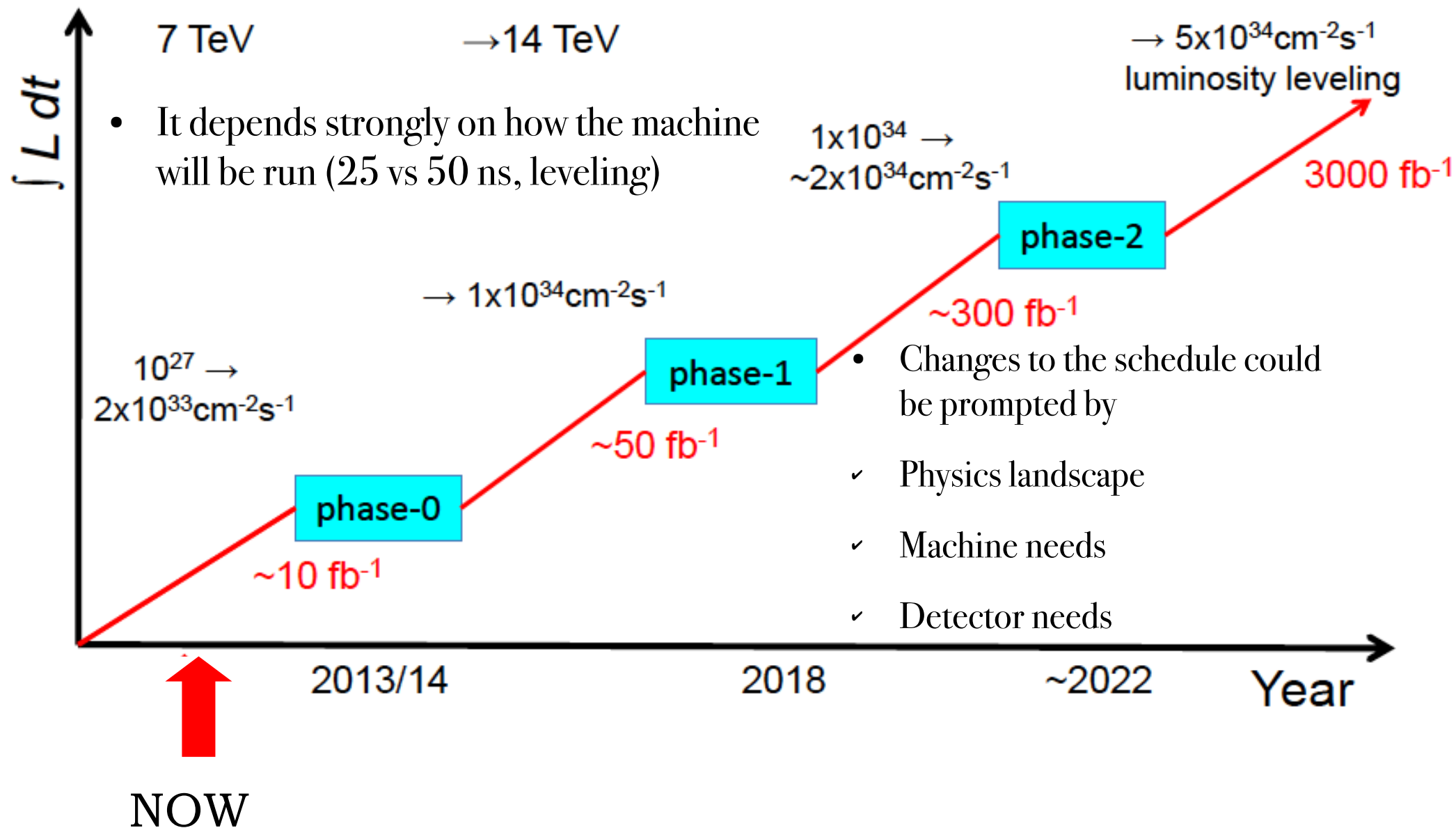
Good-quality data fraction, used for analysis :  
(depends on the analysis)

90-96%

# LHC Upgrade

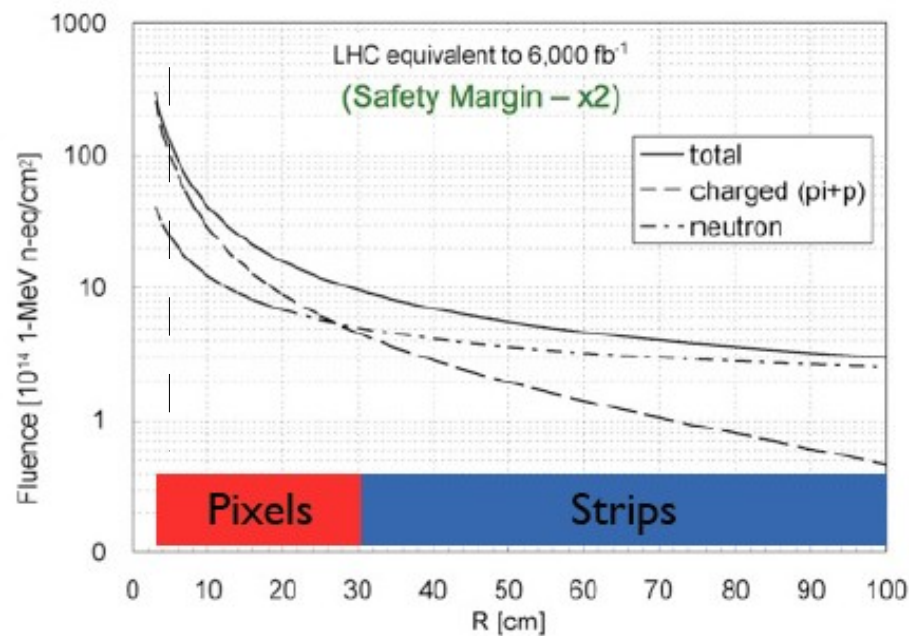
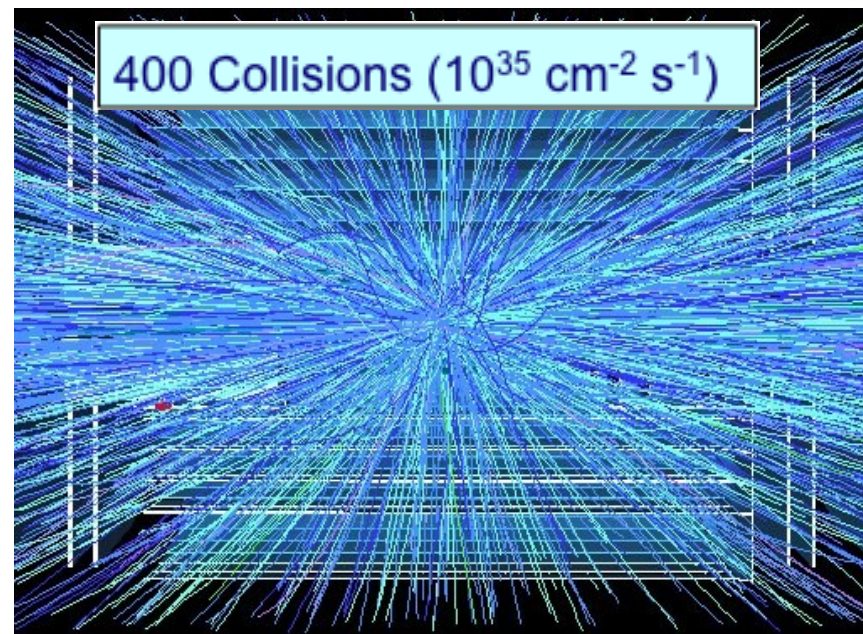
- The LHC is a discovery machine built to study:
  - **The ElectroWeak Symmetry Breaking mechanism**
  - **The shortcomings of the Standard Model**
- The discovery potential of the LHC can be enhanced by increasing its luminosity
- Infact, **whatever is discovered**, we'll want, at least, to:
  - **Improve the measurement of its properties (masses, couplings, etc)**
  - **Test further predictions of the theories put forward to explain it**

Caveat: this schedule spans decades



- Why working now for the phase-2 upgrade?
- Everybody who took part to the design of an experiment knows that it takes several years (the construction and installation itself is typically 5-6 years, after the R&D and design phase is finished). **Time flows fast!**
- LHC will not be the same between now and 2020.  
Radical improvements with respect to the initial detector (“Phase I upgrade”)

- Effects due to peak luminosity:
  - High event rate and pile-up
  - Increased occupancy
- **Higher granularity sensors**
- **Faster electronics**
- Effects due to integrated lum.:
  - Increase in leakage current
  - Change in operational voltage
  - Reduced charge collection
- **Rad-hard components**



## Change of leakage current

- can be helped with cooling

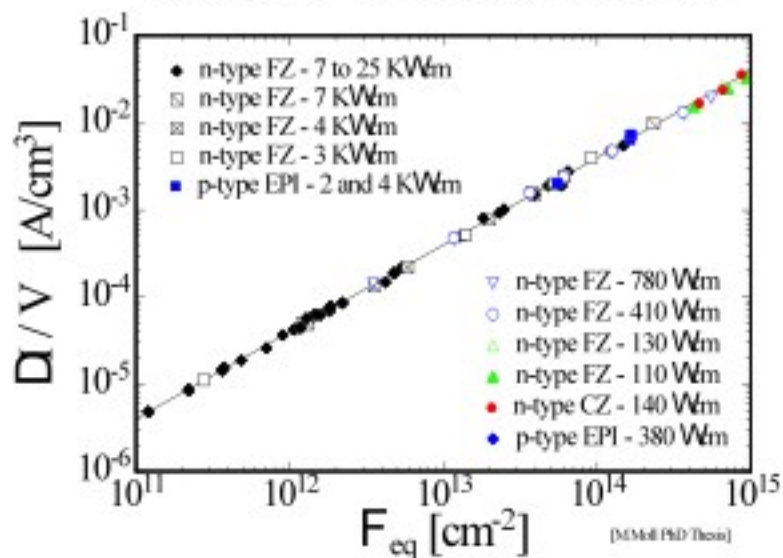
## Change of the full depletion voltage $V_{dep}$ (effective doping concentration $N_{eff}$ ).

- every p-n-junction has a finite breakdown voltage

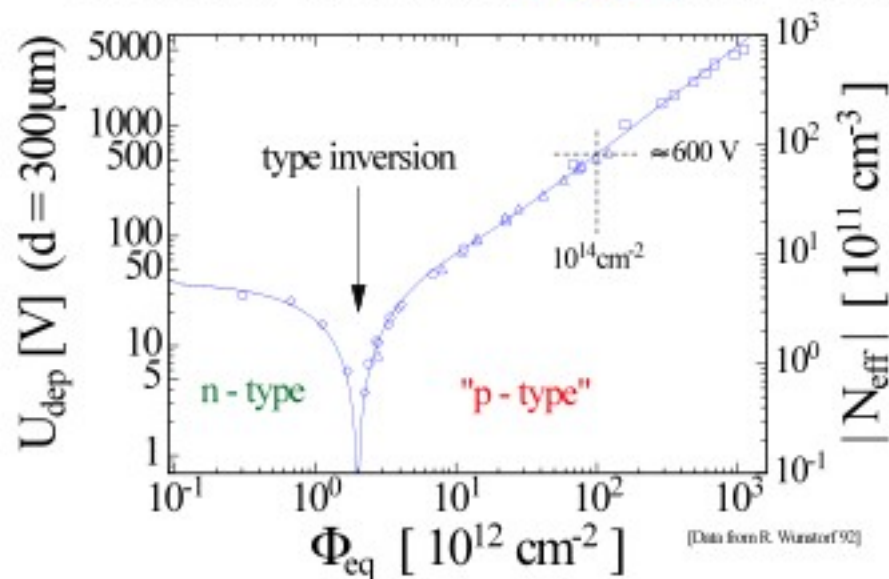
## Decrease of the charge collection efficiency

- limited by partial depletion, trapping, type inversion

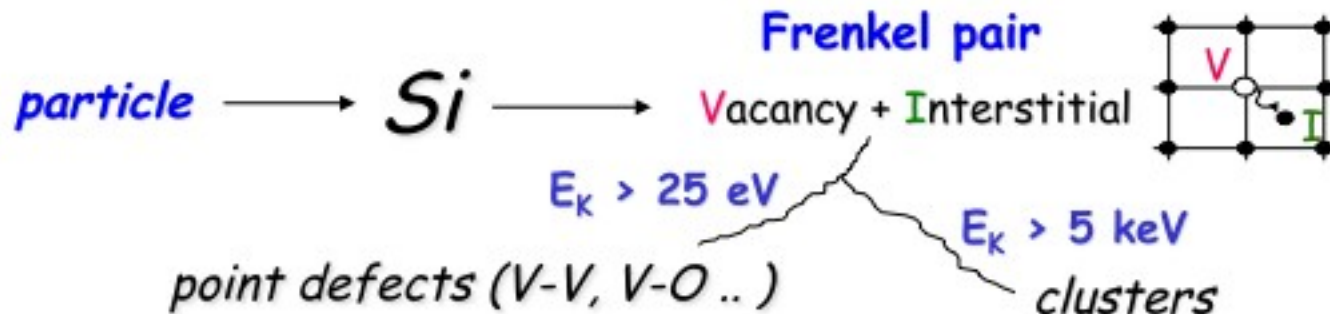
Change of the leakage current:



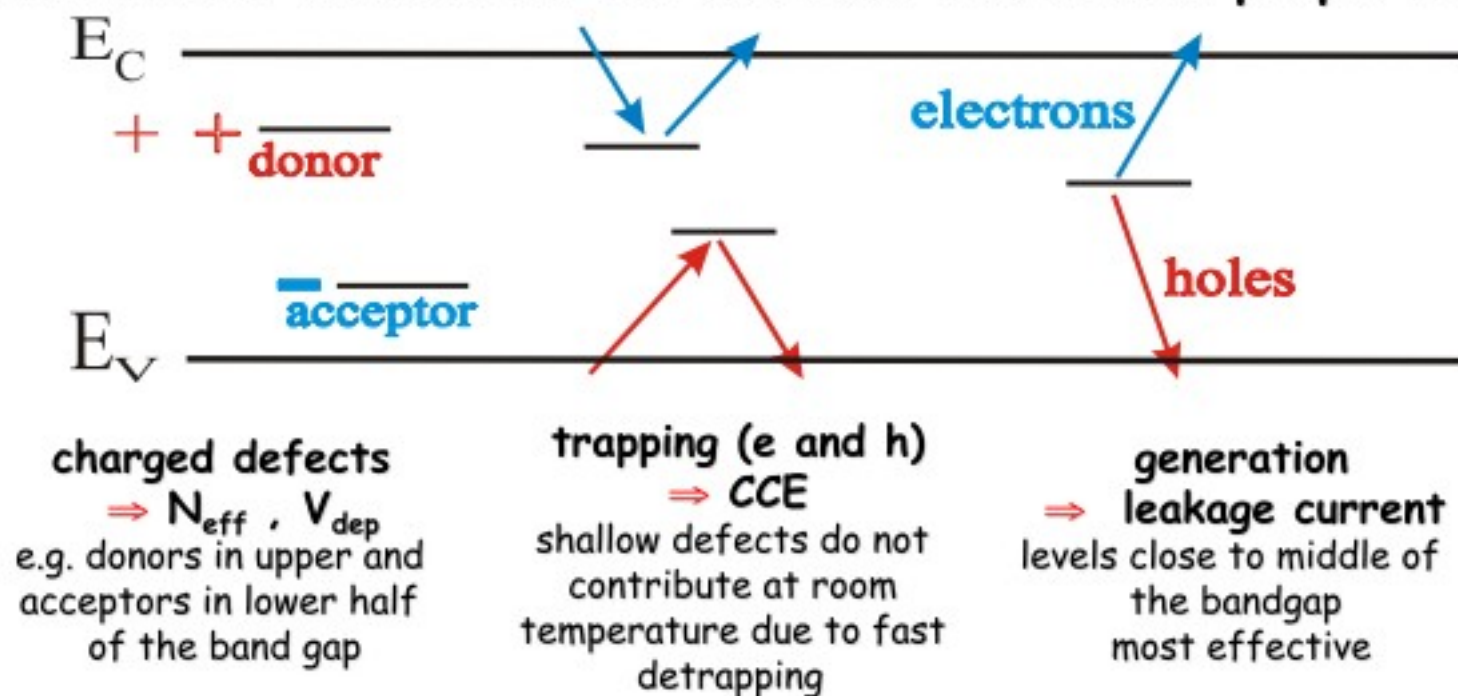
Evolution of the  $N_{eff}$  for **n-type** initial doping:



Panja Luukka, The Fifth International Forum on Advanced Material Science and Technology (IFAMST5 2006)

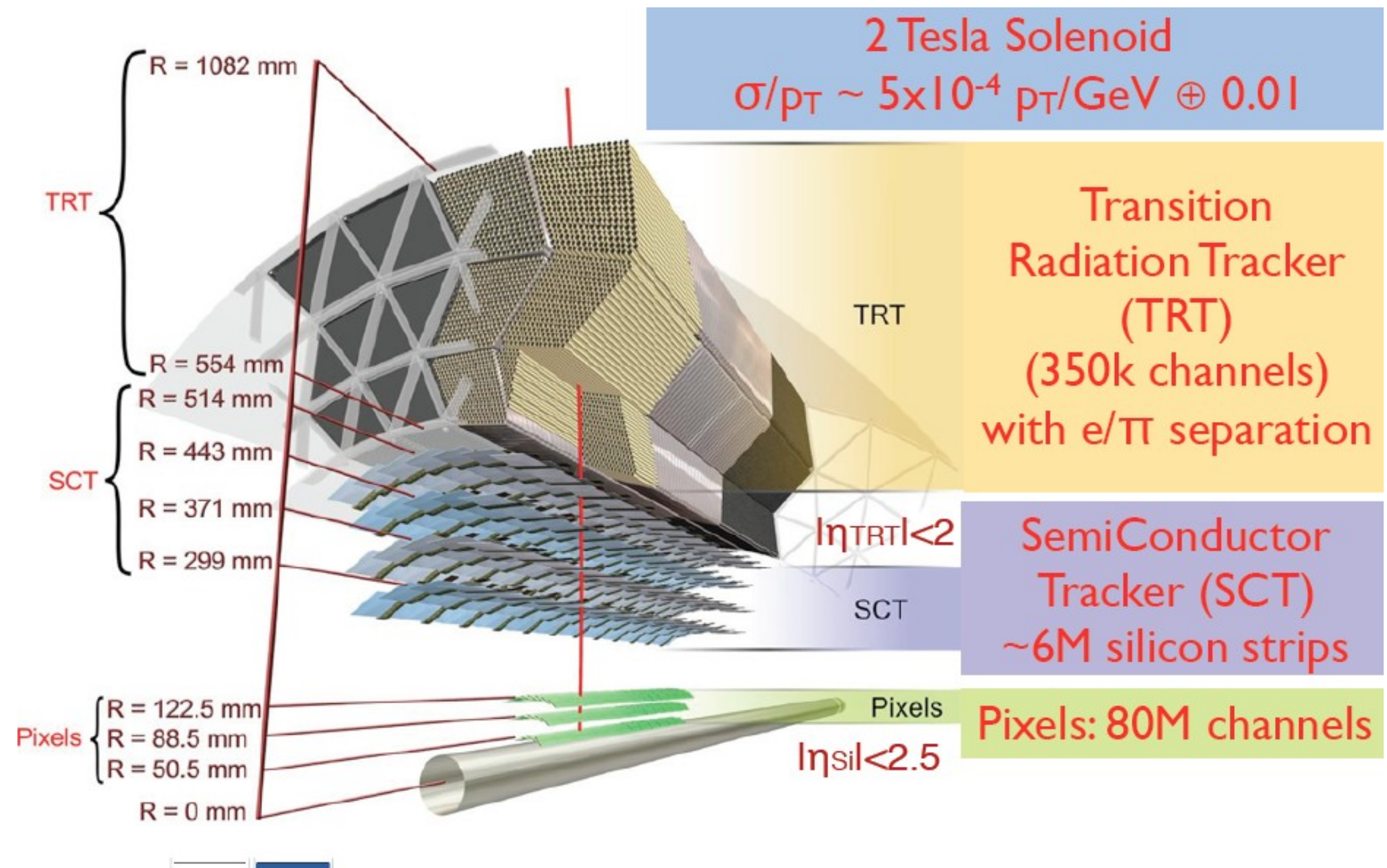


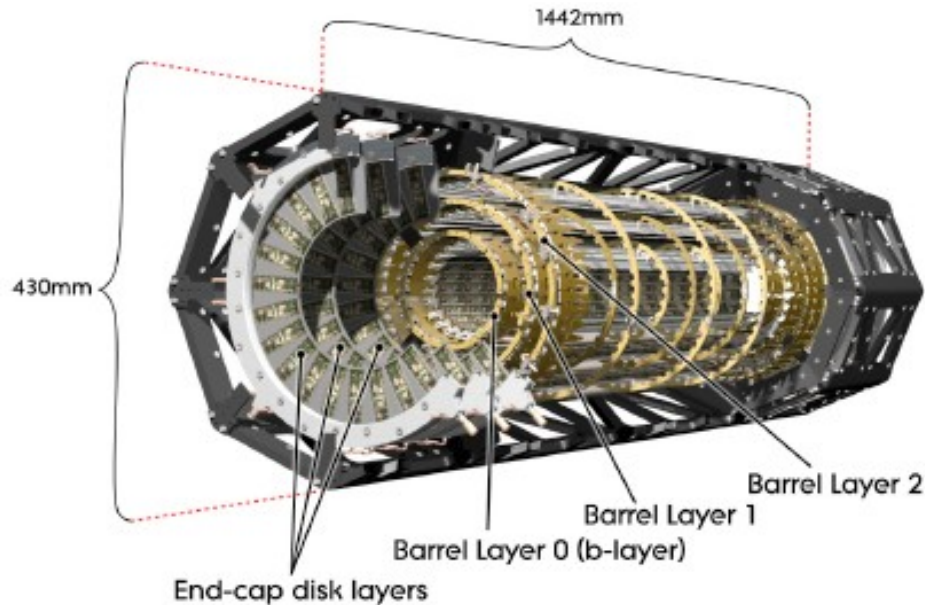
## Influence of defects on the material and device properties



Panja Luukka, The Fifth International Forum on Advanced Material Science and Technology (IFAMST5 2006)

# The Pixel Upgrade





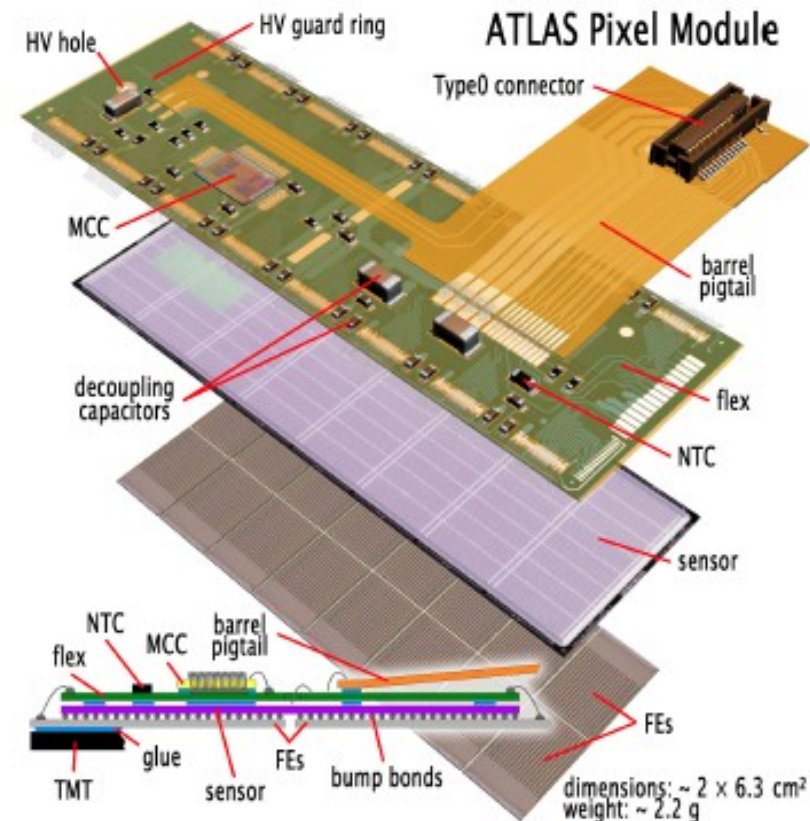
## • ATLAS Pixel Module

- 16 front-end chips (FE-I3) module with a Module Controller Chip (MCC)
- 46080 R/O channels  $50\ \mu\text{m} \times 400\ \mu\text{m}$  ( $50\ \mu\text{m} \times 600\ \mu\text{m}$  for edge pixel columns between neighbour FE-I3 chips)
- Planar n-in-n DOFZ silicon sensors, 250 $\mu\text{m}$  thick
- Designed for  $1 \times 10^{15}$  1MeV fluence and 50 Mrad
- Optolink R/O: 40÷80 Mb/link

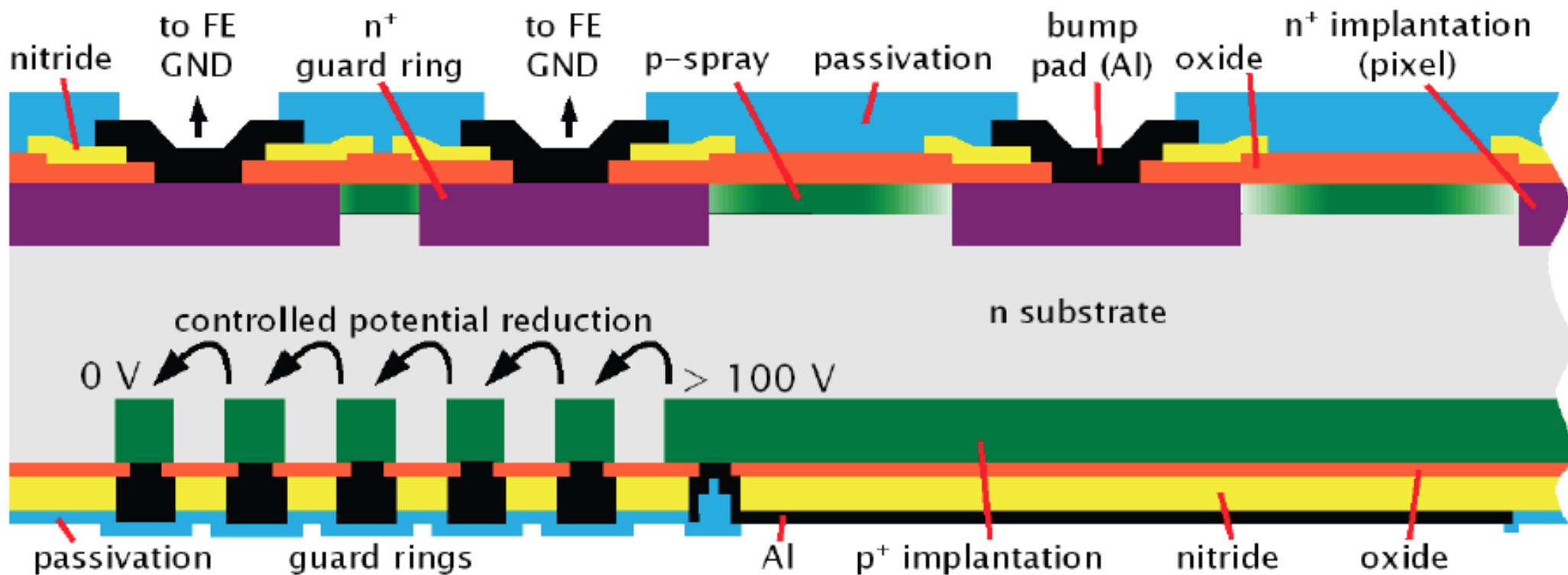
IPRD10, Siena 9.6.2010 - Alessandro La Rosa (CERN)

## • ATLAS Pixel Detector

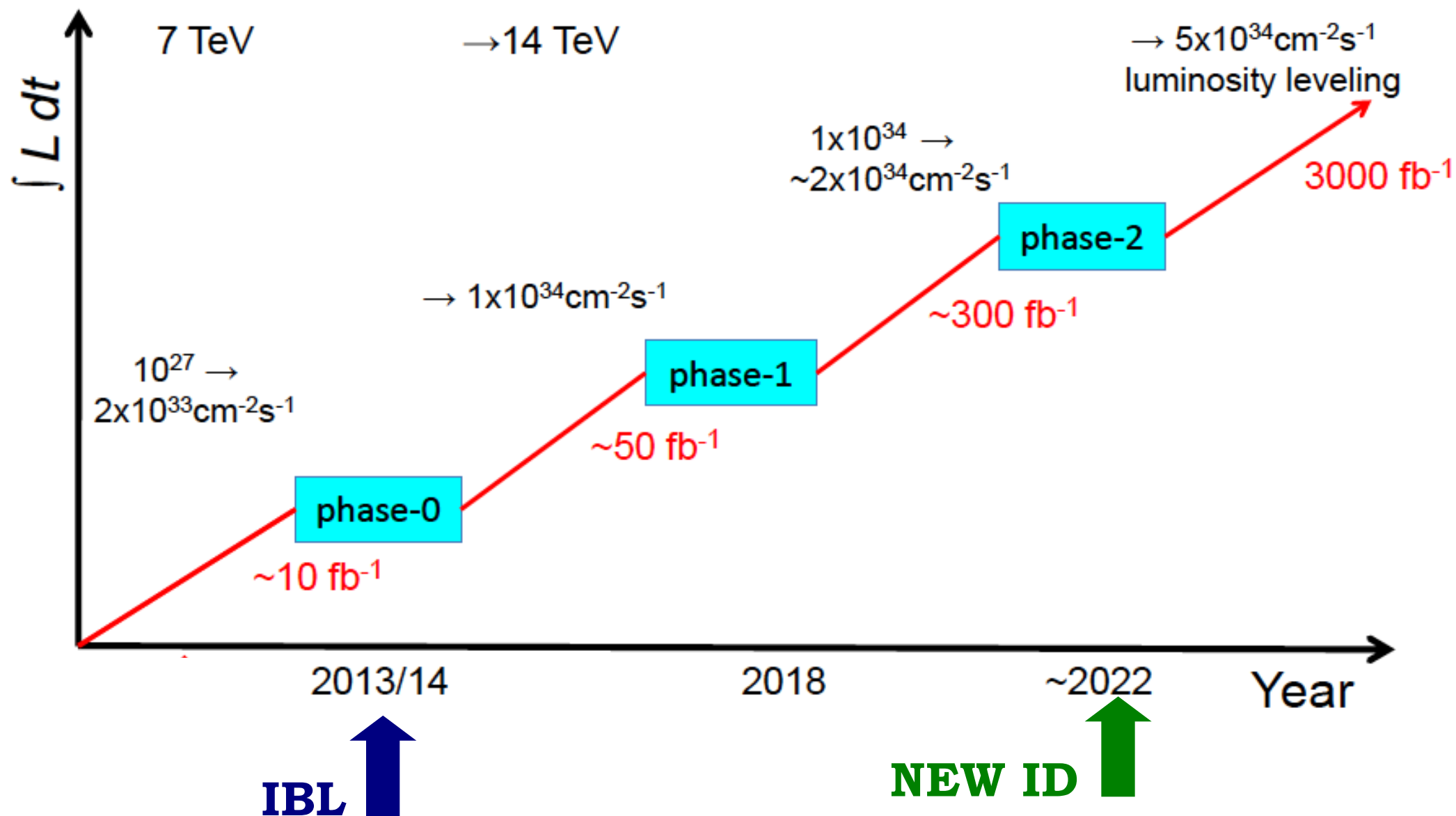
- 3 barrels + 3 forward/backward disks
- 112 staves and 4 sectors
- 1744 modules
- 80 million channels



## Schematic Layout of the ATLAS Pixel Sensor



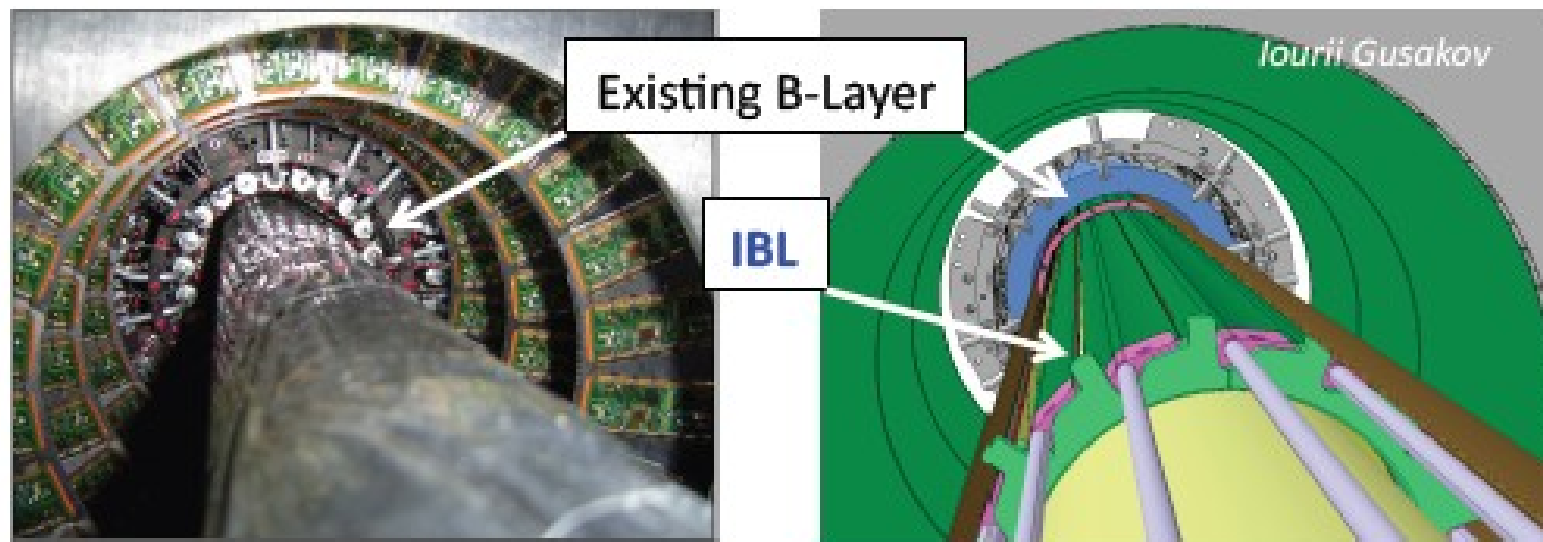
# ATLAS ID upgrade



# The Insertable B-Layer

# A 4<sup>th</sup> pixel Layer: IBL

- Adding a 4<sup>th</sup> pixel layer inside the present B-Layer: the insertable B-Layer



- To improve the performance of the existing system
- To maintain performance of existing system when present B-layer starts degrading

**Scheduled for 2013**

## • Operation:

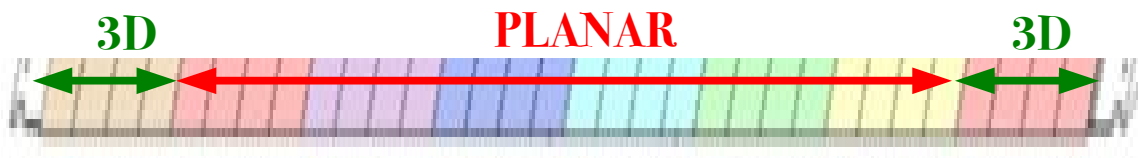
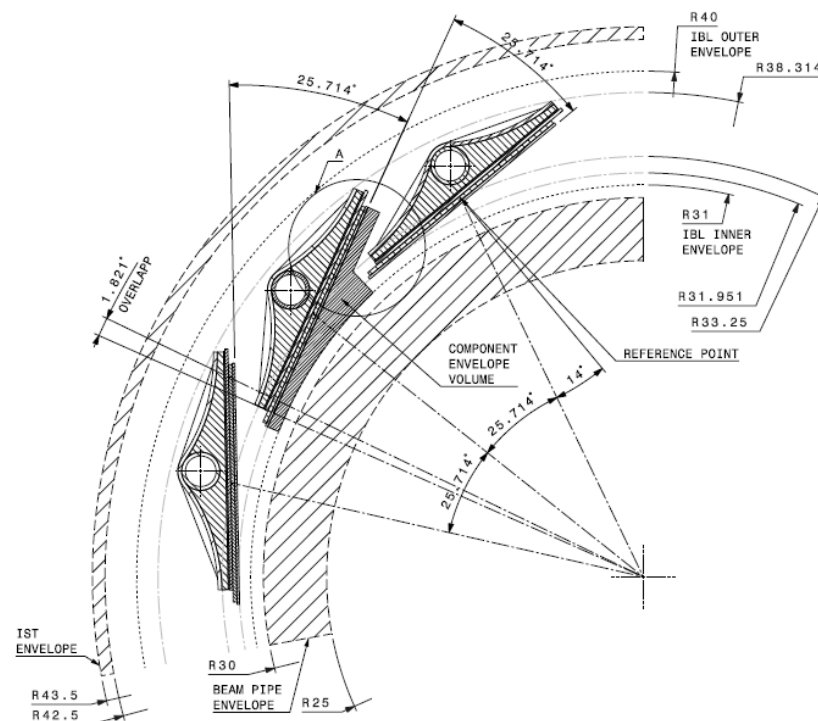
- 14 Staves @  $R=3.3$  cm,  $|\eta| < 2.5$ ,  $0.2$  m<sup>2</sup>
- No overlap on Z due to space restriction
- Operate at -15 C, CO<sub>2</sub> cooling

## • Front-end/Sensor Design:

- NIEL dose =  $5 \times 10^{15} n_{eq} \text{ cm}^{-2}$  (w/ safety factor)
- Ionizing dose  $\geq 250$  Mrad
- Small dead area (slim/active edge)
- Max sensor power  $< 200 \text{ mW/cm}^2$  @ -15 C
- Max bias voltage: 1000V

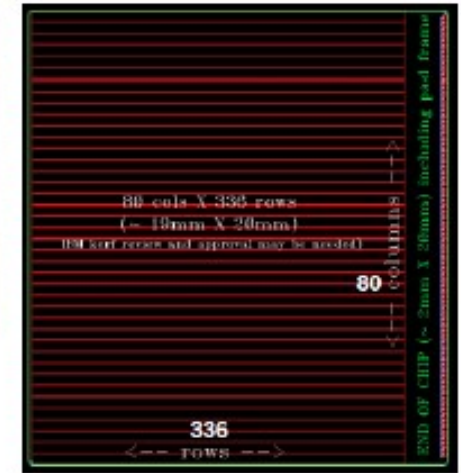
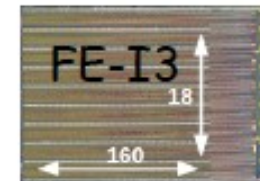
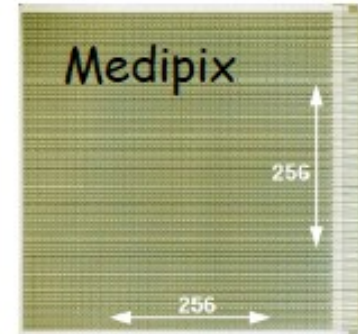
## • Sensor Technology

- Planar n-on-n and 3D double sided being considered
- 75% Planar and 25% 3D sensor layout



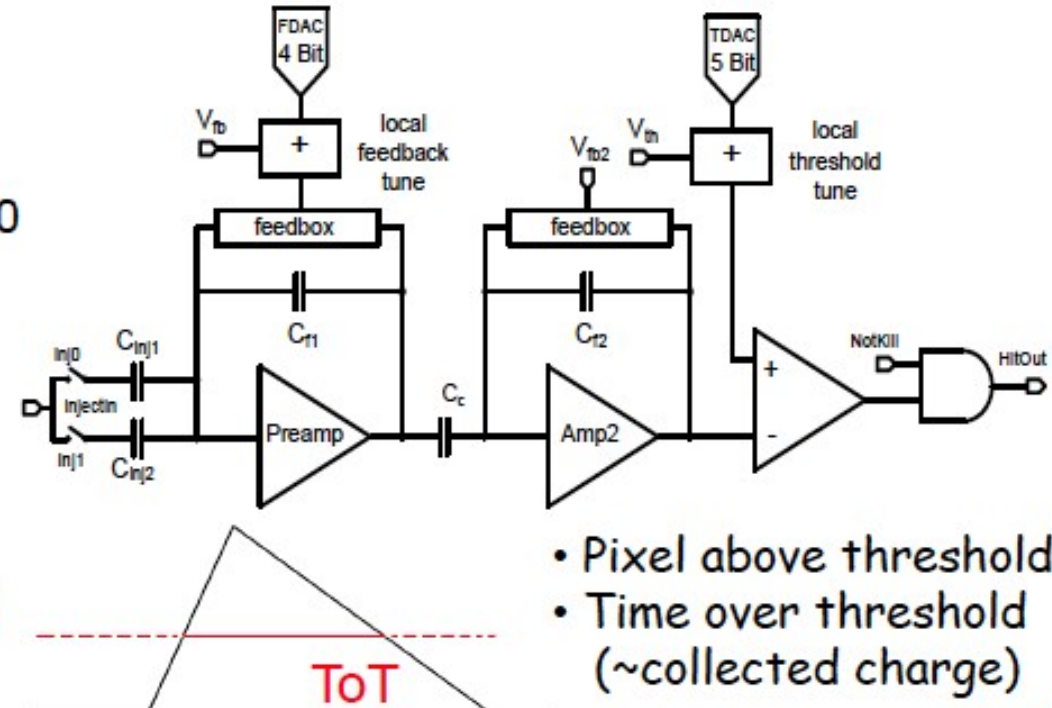
# IBL: Font End Chip: FE-I4 ("A")

- Biggest chip in HEP to date
- Higher active fraction (x6)  
(than ATLAS predecessor)
- Local memory cells (bus activity only on readout) → Lower power
- Higher data rate
- More radiation hard (130nm technology)



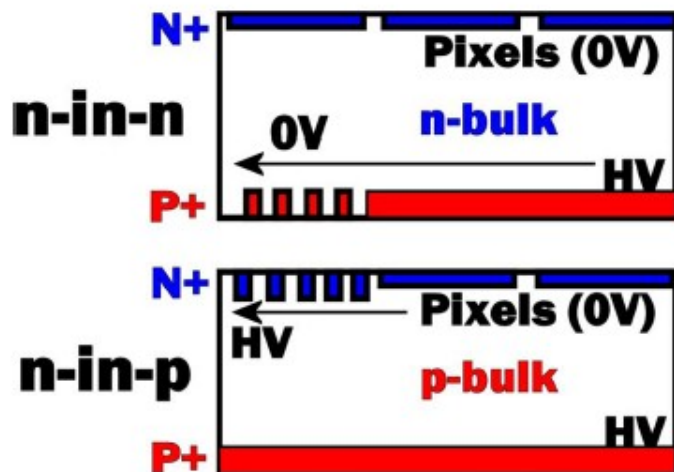
FE-I4

Pixel array	80x336
Chip size (mm <sup>2</sup> )	20.2x19.0
Active fraction (%)	89
Analog/Digital current (uA/pix)	10/10
Analog/Digital voltage (V)	1.5/1.2
LVDS output (Mb/s)	160
Pixel size (um <sup>2</sup> )	50 x 250
ToT Resolution	4-bit



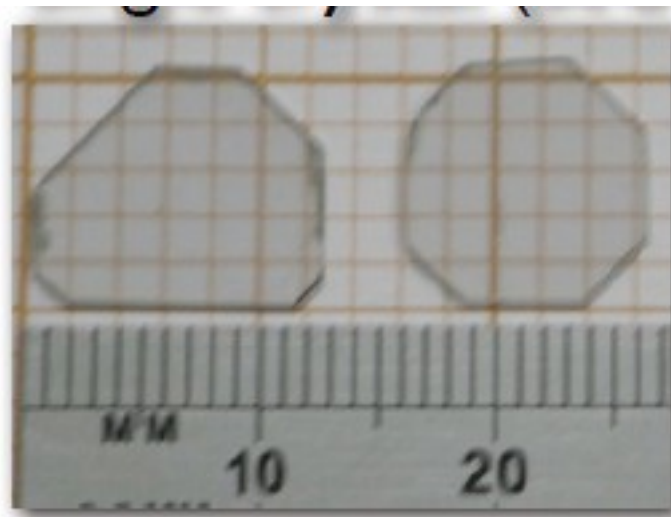
# Beyond 2020: The Planar Pixel Sensor Project

## PLANAR



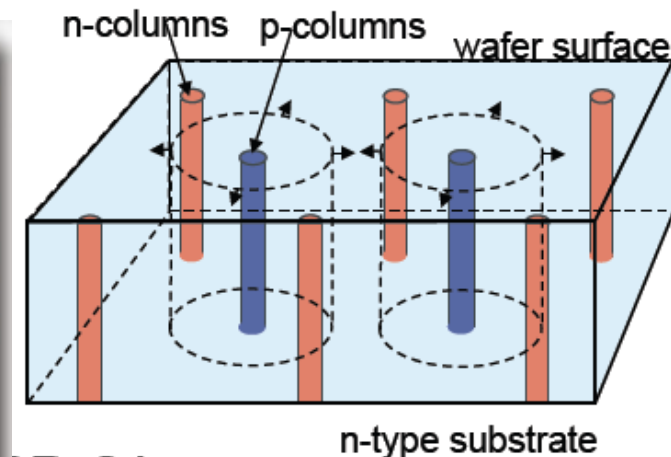
- More details in the next slides

## DIAMOND




- Very low noise
- No cooling
- No doping needed
- Low capacitance
- Very high BD field
- Expensive
- Difficult to realize large sample of single crystal sensors

## 3D



- Implants through the detector
- Highly segmented sensor
- Low depletion voltage
- Fast signal
- High rate capable
- Inefficiency regions corresponding to column
- Low cost large production to be proven

- Aim: Explore the suitability of planar pixel sensors for highest fluences
- Approved ATLAS R&D project since 2009: 17 institutes, more than 80 scientists

	<p>R&amp;D on Planar Pixel Sensor Technology for the ATLAS Inner Detector Upgrade</p>		
ATLAS Upgrade Document No:	Institute Document No.	Created: 10/01/2008	Page 1 of 19
		Modified: 07/05/2009	Rev. No.: 1.1

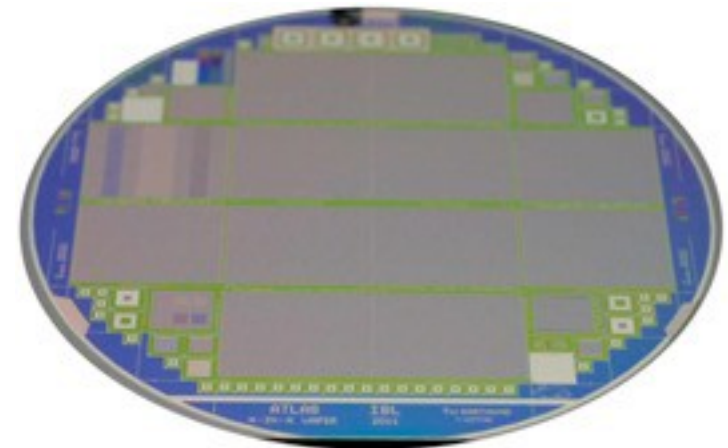
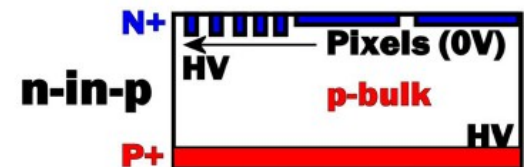
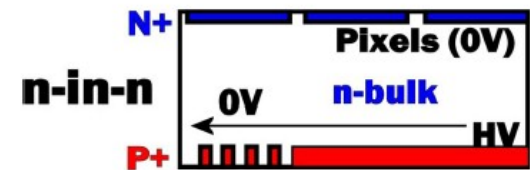
D. Dobos, B. Di Girolamo, H. Pernegger, S. Roe, A. La Rosa<sup>1</sup>, V. Vrba, P. Sicho, J. Popule, M. Tomasek, L. Tomasek, J. Stastny, M. Marcisovsky, M. Havranek, J. Bohm<sup>2</sup>, A. Lounis, N. Dinu, M. Benoît, R. Tanaka<sup>3</sup>, G. Calderini, D. Lacour, H. Lebbolo, G. Marchiori, J. Ocariz, P. Schwemling<sup>4</sup>, M. Barbero, F. Hügging, H. Krüger, N. Wermes<sup>5</sup>, H. Lacker<sup>6</sup>, I. M. Gregor, U. Husemann, P. Kostka<sup>7</sup>, C. Gößling, R. Klingenberg, D. Münstermann, A. Rummler, G. Troska, T. Wittig, R. Wunstorf<sup>8</sup>, J. Grosse-Knetter, M. George, A. Quadt, J. Weingarten<sup>9</sup>, L. Andricek, M. Beimforde, A. Macchiolo, H.-G. Moser, R. Nisius, R. Richter, P. Weigell<sup>10</sup>, D. Cauz, M. Cöbal, C. del Papa, D. Esseni, M. P. Giordani, P. Palestri, G. Pauletta, L. Selmi<sup>11</sup>, Y. Unno, S. Terada, Y. Ikegami<sup>12</sup>, M. Cavalli, I. Korolkov, M. Lozano, C. Padilla, G. Pellegrini, M. Ullan<sup>13</sup>, T. Affolder, P. Allport, G. Casse, T. Greenshaw, I. Tsurin<sup>14</sup>, M. Battaglia, T. Kim, S. Zalusky<sup>15</sup>, I. Gorelov, M. Hoferkamp, S. Seidel, K. Toms<sup>16</sup>, V. Fadeyev, A. Grillo, J. Nielsen, H. Sadrozinski, B. Schumm, A. Seiden<sup>17</sup>

17 institutions:

<sup>1</sup>CERN, <sup>2</sup>AS CR, Prague, <sup>3</sup>LAL Orsay/ University Paris-sud XI, <sup>4</sup>LPNHE / University Paris VI, <sup>5</sup>University of Bonn, <sup>6</sup>HU Berlin, <sup>7</sup>DESY, <sup>8</sup>TU Dortmund, <sup>9</sup>University of Goettingen, <sup>10</sup>MPP and HLL Munich, <sup>11</sup>Università degli Studi di Udine – INFN, <sup>12</sup>KEK, <sup>13</sup>IFAE-CNM (Barcelona), <sup>14</sup>University of Liverpool, <sup>15</sup>UC Berkeley/LBNL, <sup>16</sup>UNM, Albuquerque, <sup>17</sup>UCSC, Santa Cruz

# Why planar sensors?

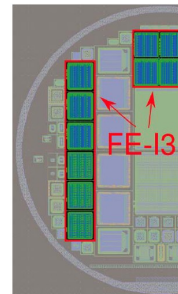
- Planar pixel is a proven technology
  - The current n-in-n pixel detector.
  - Modules shown to work after  $10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
  - If strips not adequate any more, pps would be the natural option
- Potential for a low-cost large-area production with n-in-p
  - Only one side is patterned
- Research directions
  - Advanced simulation studies
  - Active area optimization and geometry redesign
  - Radiation damage studies
  - High rate capable electronics
  - Low cost module production



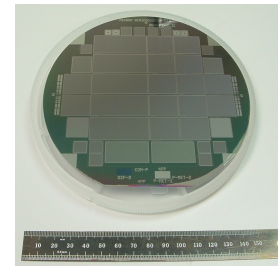
# PPS working “tools”

- Different sensors,  
n- & p-type bulk  
both FEI3 and FEI4

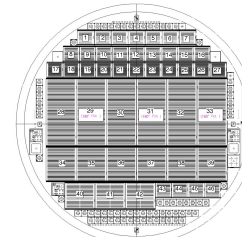
CiS



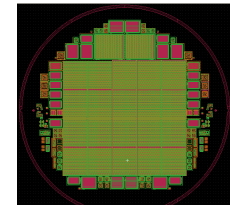
Micron



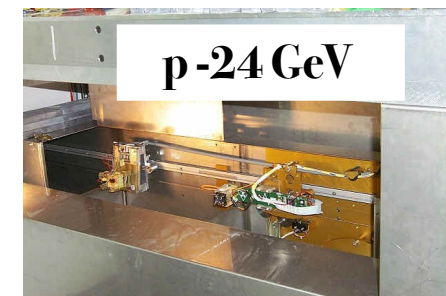
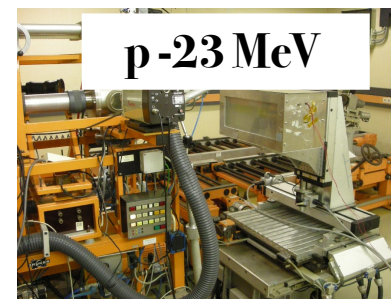
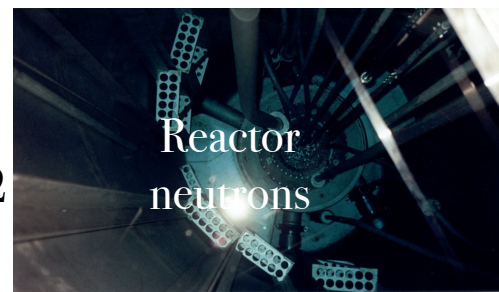
HPK



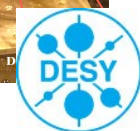
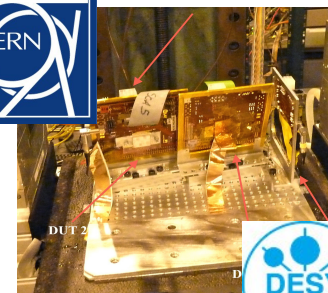
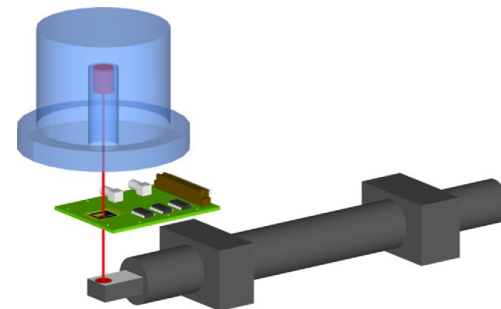
MPI-HLL



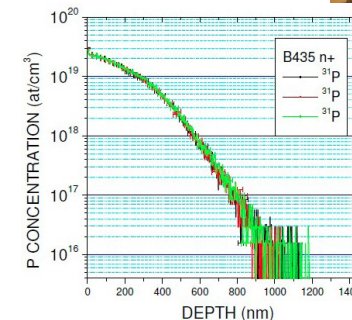
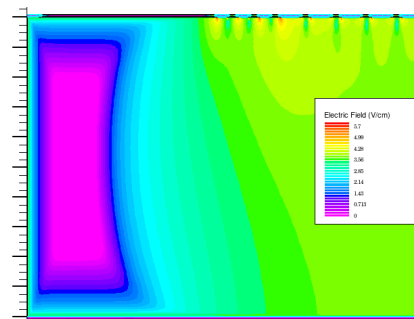
- n&p irradiation  
up to  $2 \times 10^{16} n_{eq}/cm^2$



- Lab characterization  
& beam tests



- TCAD simulations along  
with precise inputs

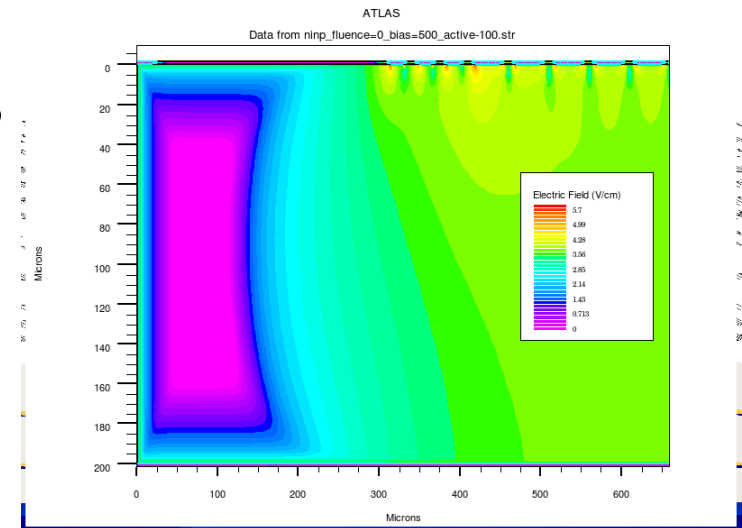


- Technology Computer Aided Design offers the possibility to simulate the behavior of a sensor under several conditions

- Reverse bias
- Illuminated by light
- At high/low temperature
- As been exposed to high fluences

Simulation saves you money  
but needs very precise inputs to  
produce reliable information

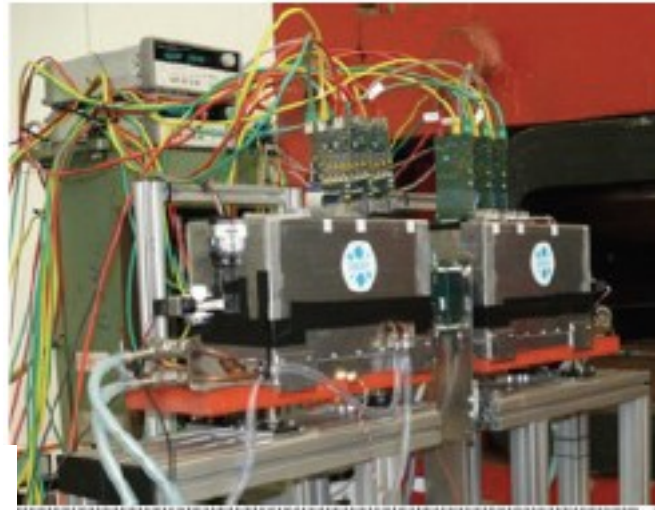
- And monitor the interesting quantities
  - IV / CV curves
  - GR potentials
  - CCE
  - Electric field



- Sensors bonded to FEI3 or FEI4 ROCs are tested in the laboratory with the help of radioactive sources and in a beam test setup equipped with a beam telescope which allows

tracking

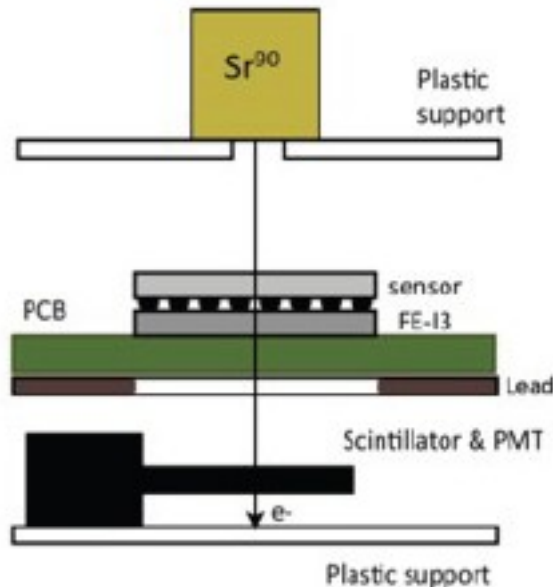
Single chip adapter  
card w/ sensor + FE



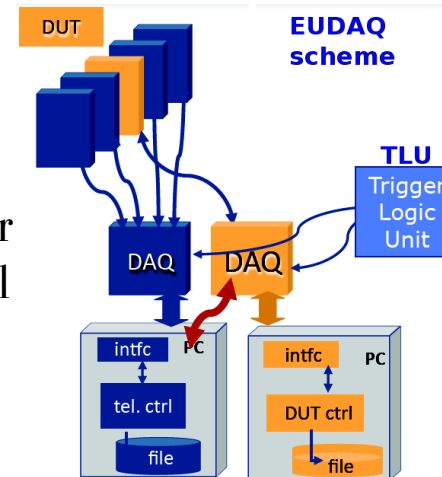
Test beam:

- hit maps
- energy deposition
- efficiencies
- spatial resolution

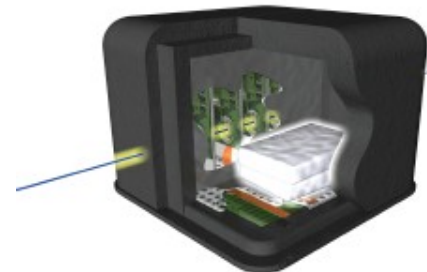
Source scans:  
hit maps &  
energy deposition



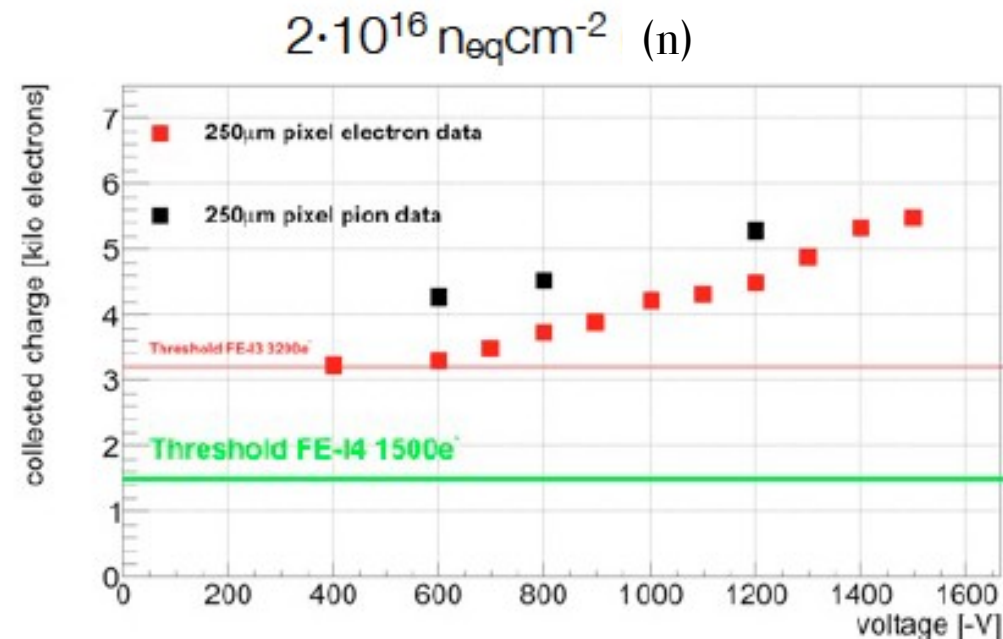
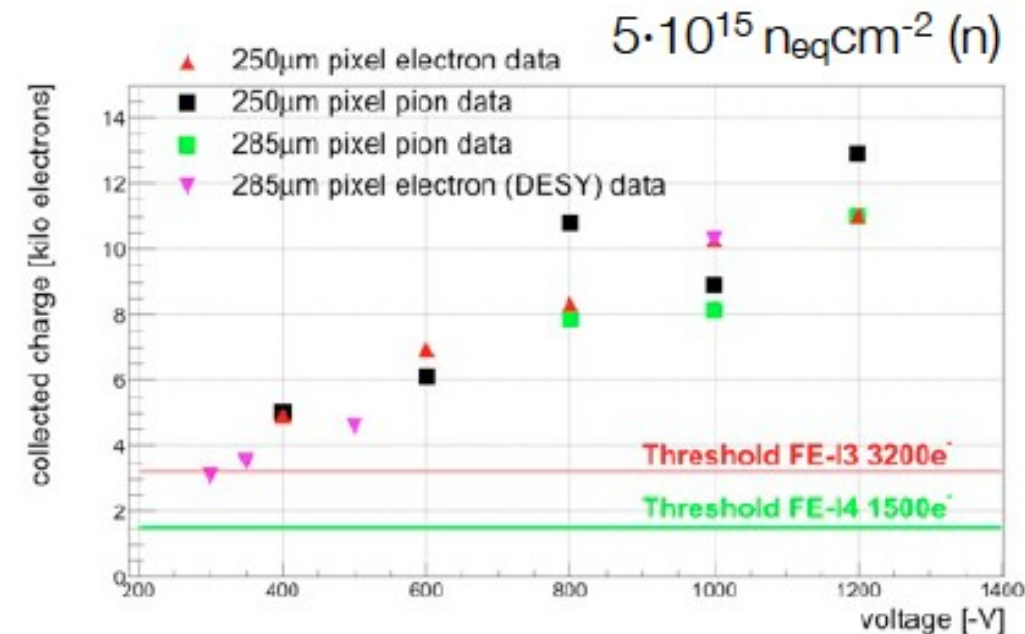
One or  
several  
DUTs



Cooling  
system

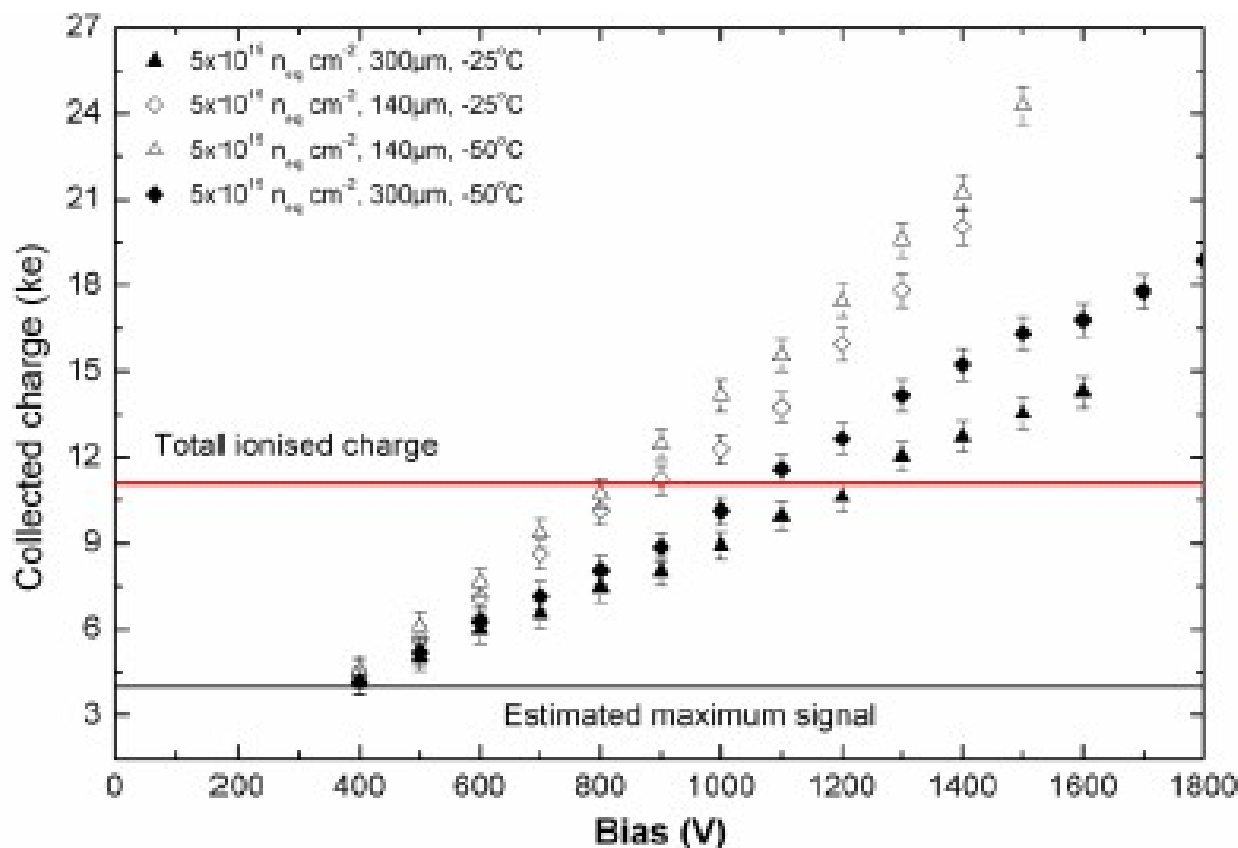


- **Status** ATLAS pixels modules were shown to be rad-hard up to  $10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
- **Goal:** test further their radiation tolerance, up to  $2 \times 10^{16} \text{ n}_{\text{eq}}/\text{cm}^2$
- ➔ **Method:** n-irradiated ( $\Phi$  up to  $2 \times 10^{16} \text{ n}_{\text{eq}}/\text{cm}^2$ ) ATLAS modules tested with  $\beta$  from source and  $\pi/e$  beams



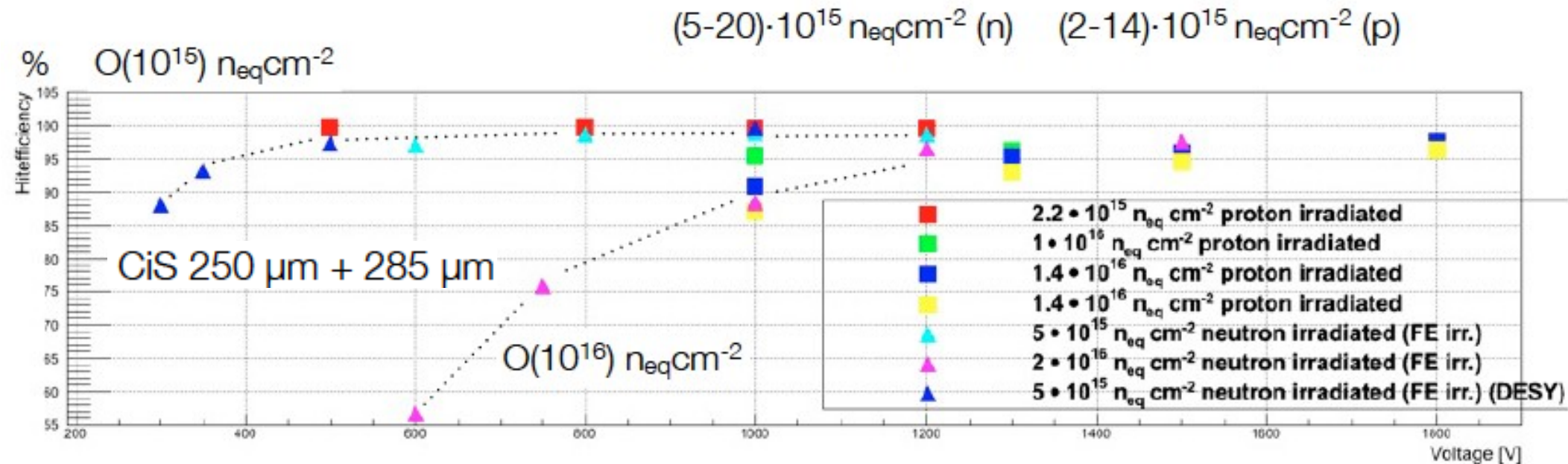
➔ **Result:** Charges are higher than model predictions which include trapping

→ 140 and 300  $\mu\text{m}$  n-in-p Micron sensors after  $5 \times 10^{15} \text{ n}_{\text{eq}}$  26MeV protons



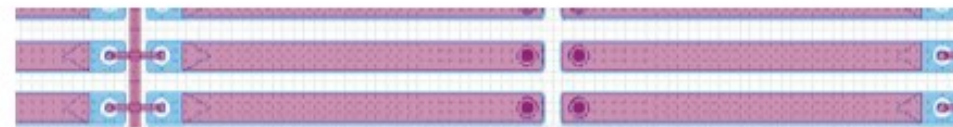
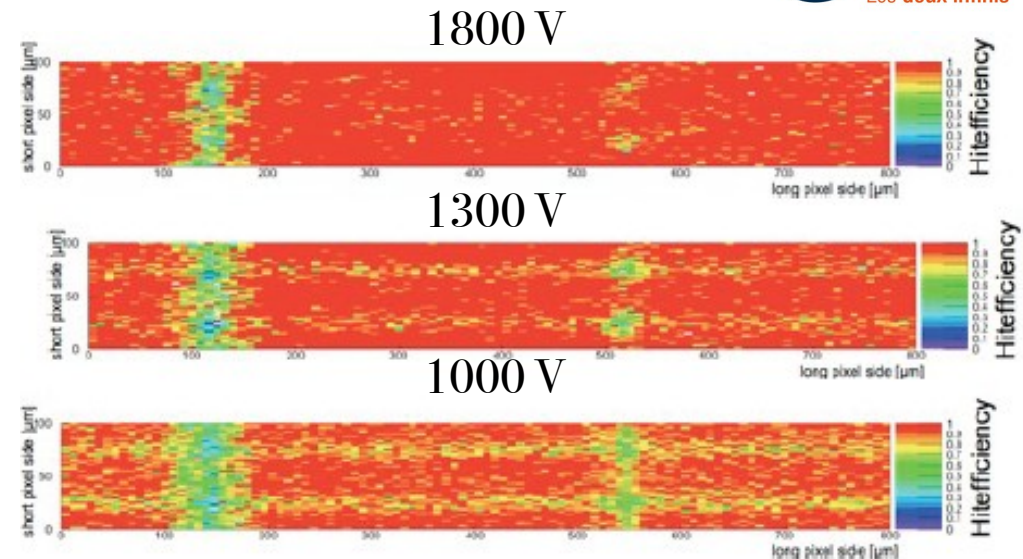
✓ Evidence of a charge multiplication effect: not only the whole charge is recovered, but increased by  $f = 1.75$

- **Status:** after irradiation the full depletion voltage changes → bulk could be only partially depleted
- **Goal:** fully recover the hit efficiency
- ➔ **Method:** increase bias voltage for n-&p-irradiated modules



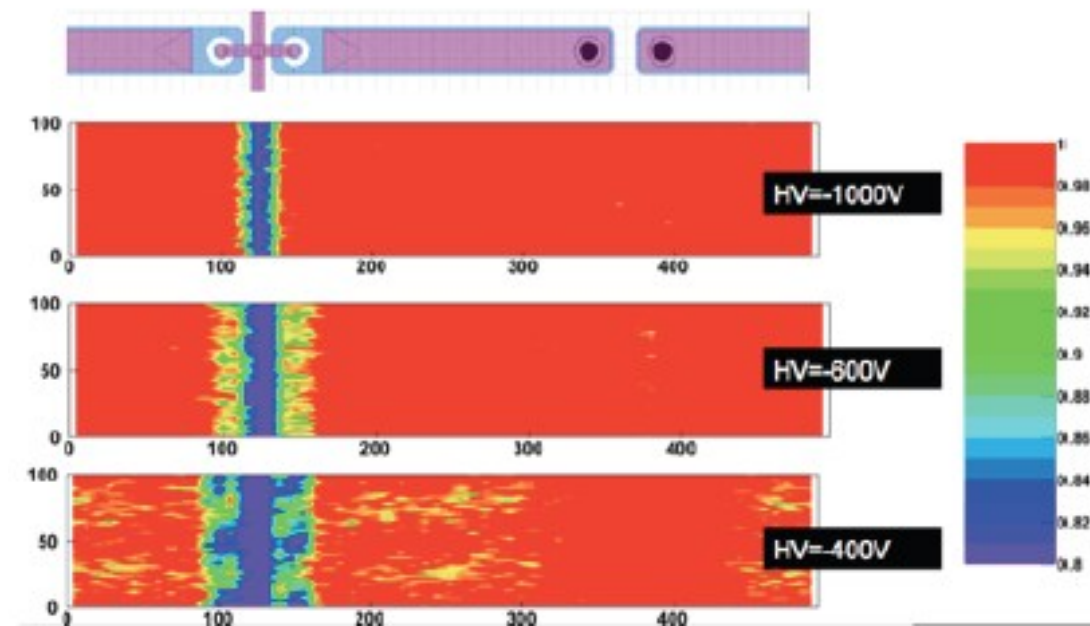
- ✓ **Result:** efficiency recovered at  $V_{bias} = 1000V$  for fluences up to  $5 \cdot 10^{15} n_{eq} / cm^2$  and very promising results for  $\Phi \sim O(10^{16} n_{eq} / cm^2)$

- **Goal:** identify in-efficient regions inside the pixel cell
- ➔ **Method:** test on beam irradiated device ( $4 \times 10^{15} n_{eq}/cm^2$  (n),  $250 \mu m$ ), studying their efficiency as a function of the  $V_{bias}$
- ✓ **Result:**  $\langle \epsilon \rangle > 97\%$  @ 600V

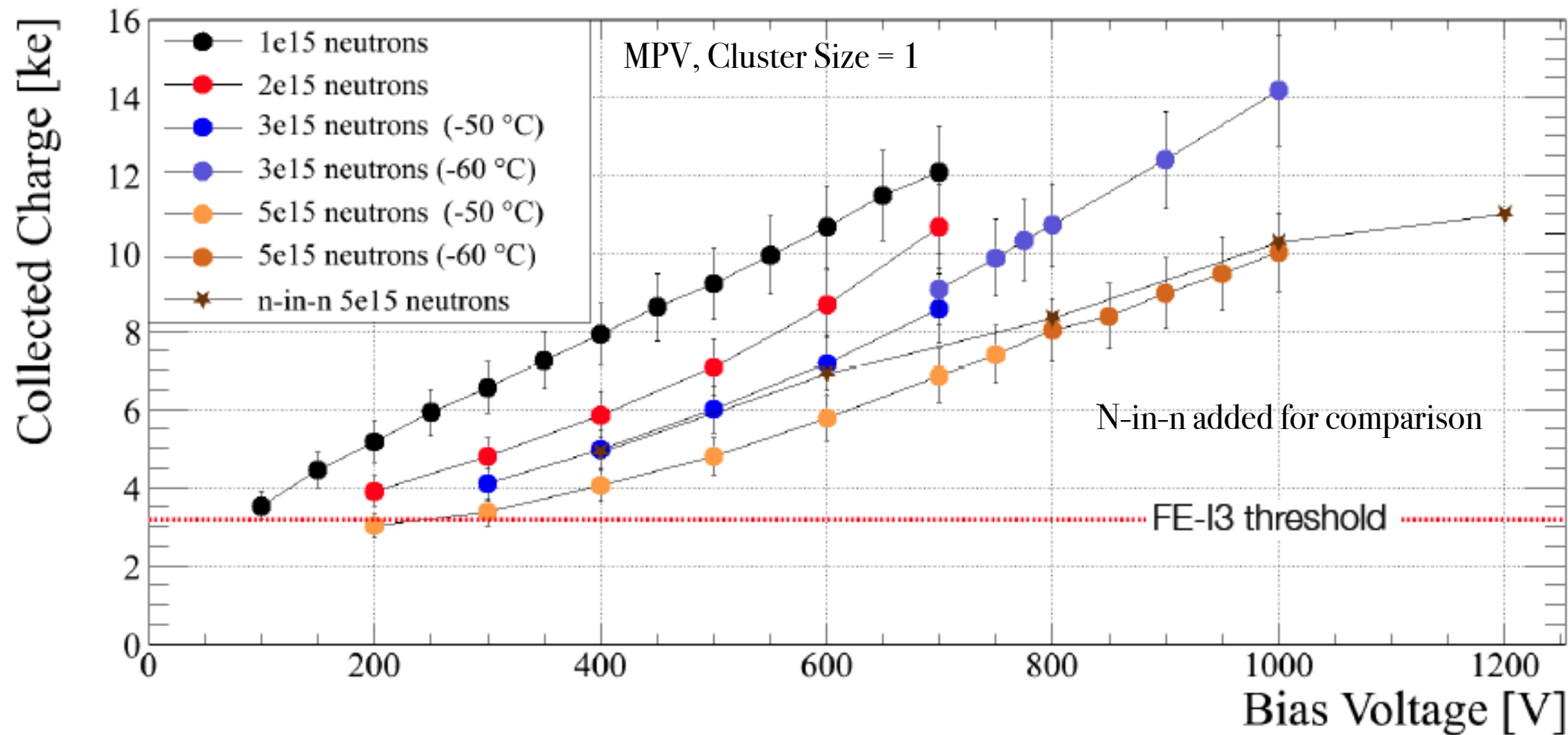


- ➔ **Method:** test on beam irradiated device ( $1.4 \times 10^{16} n_{eq}/cm^2$  (p),  $250 \mu m$ ), studying their efficiency as a function of the  $V_{bias}$

- ✓ **Result:**  $\langle \epsilon \rangle > 97\%$  @ 1800V

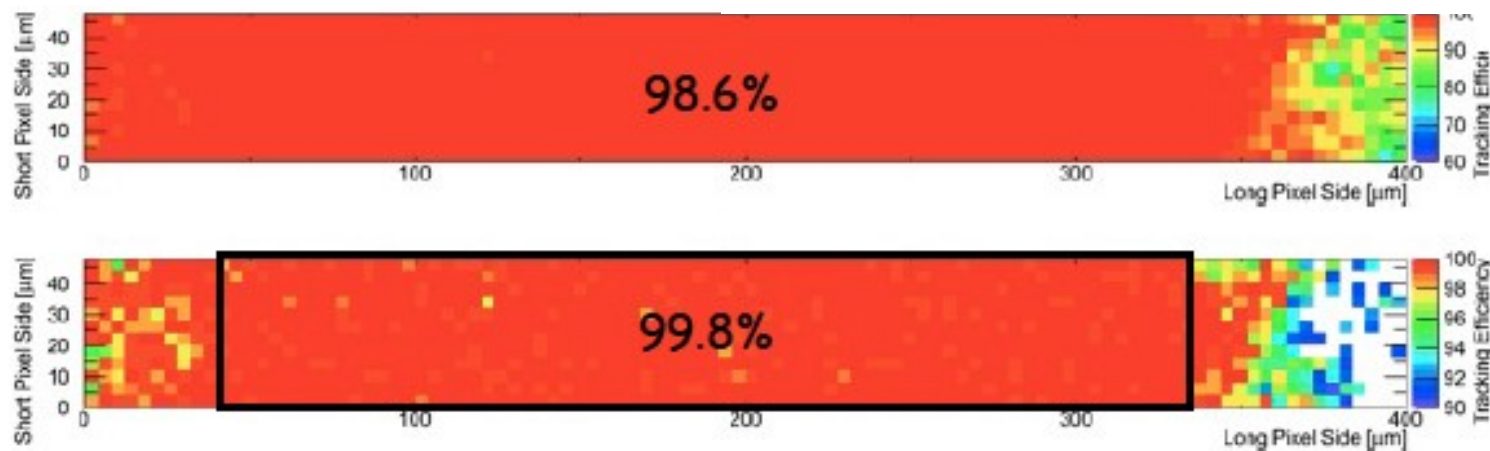
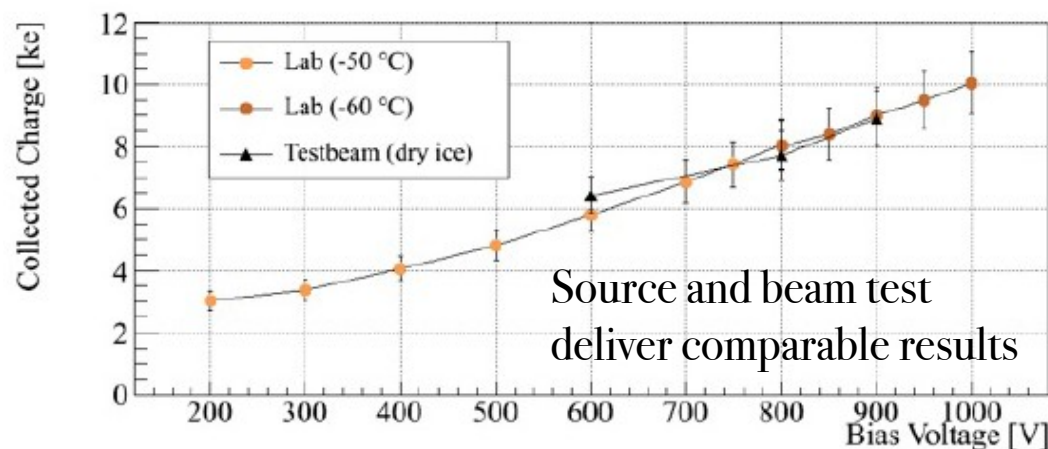


- **Goal:** test charge collection for p-bulk detectors at  $\Phi \sim O(10^{15} n_{eq}/cm^2)$
- ➔ **Method:** 285  $\mu m$  thick n-in-p sensors, n-irradiated, tested with radioactive source



✓ **Result:** significant charge is collected above threshold,  $V_{bias} > 600 V$

- **Goal:** identify in-efficient regions inside the pixel cell
- ➔ **Method:** 300  $\mu\text{m}$  thick, neutron-irradiated @  $5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$



## ✓ Results:

- ✓ significant charge is collected above threshold
- ✓ overall efficiency :98.6%;
- ✓ losses around bias dot; higher efficiency in the center of the pixel

# Thin bulk sensor

✓ **NEW:** first HPK n-in-p sensors, 150  $\mu\text{m}$ , 6" wafer with different pixel biasing and isolation schemes

→ Bias structure aims to reduce less-efficient area

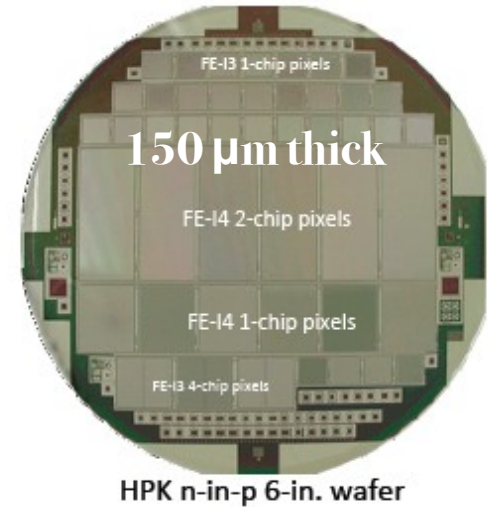
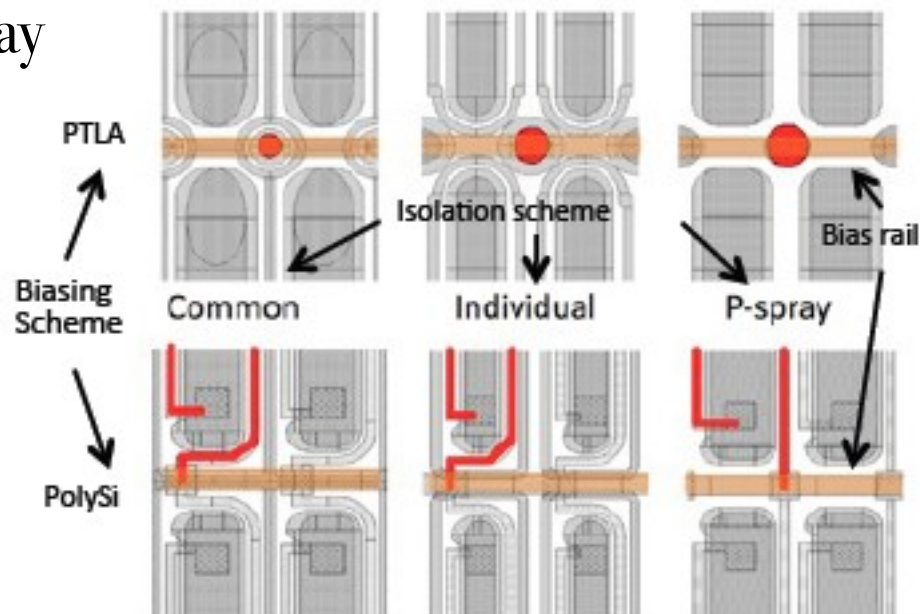
A) Punch-thru (PTLA): a bias dot in the 4-corner

B) Polysilicon: an encircling pixel implant ( $\sim 2\text{M}\Omega$ )

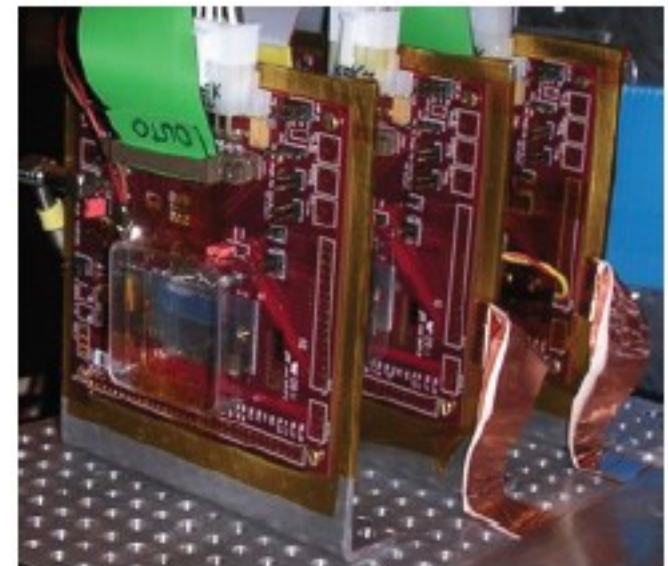
→ Isolation structure:

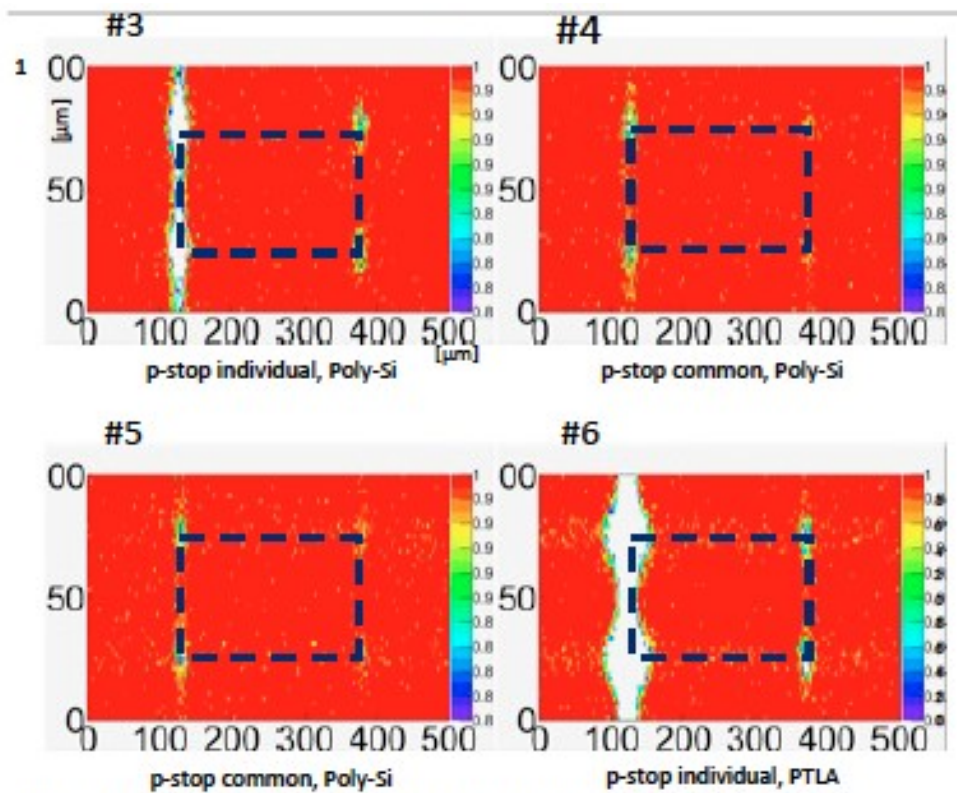
I. P-stop, common & individual

II. p-spray



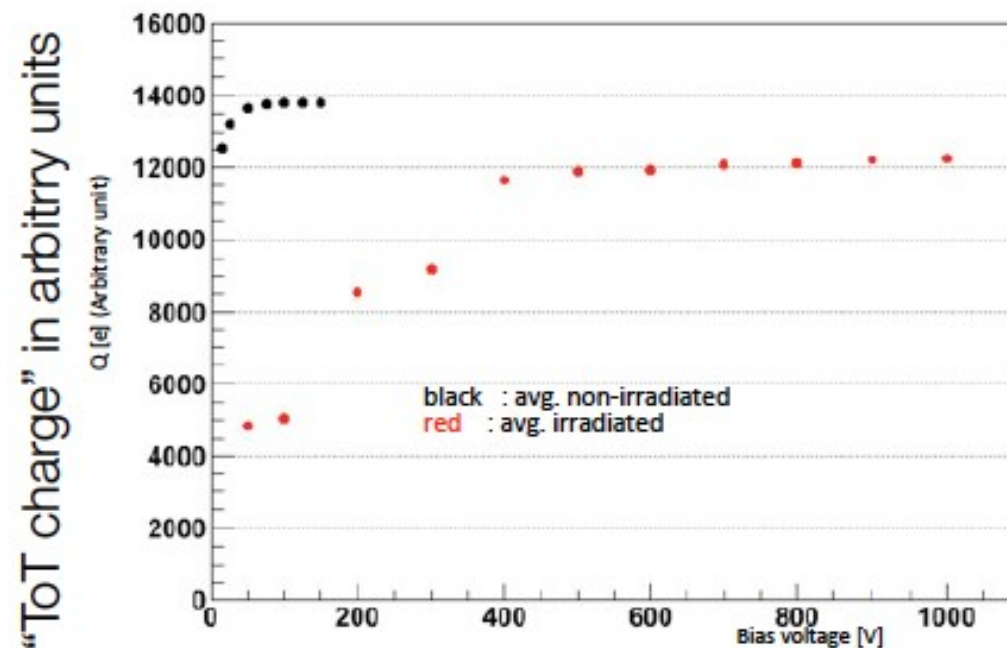
Investigated on beam.  
See next slides





2D efficiency map of a pixel, non-irrad, at 150 V bias voltage

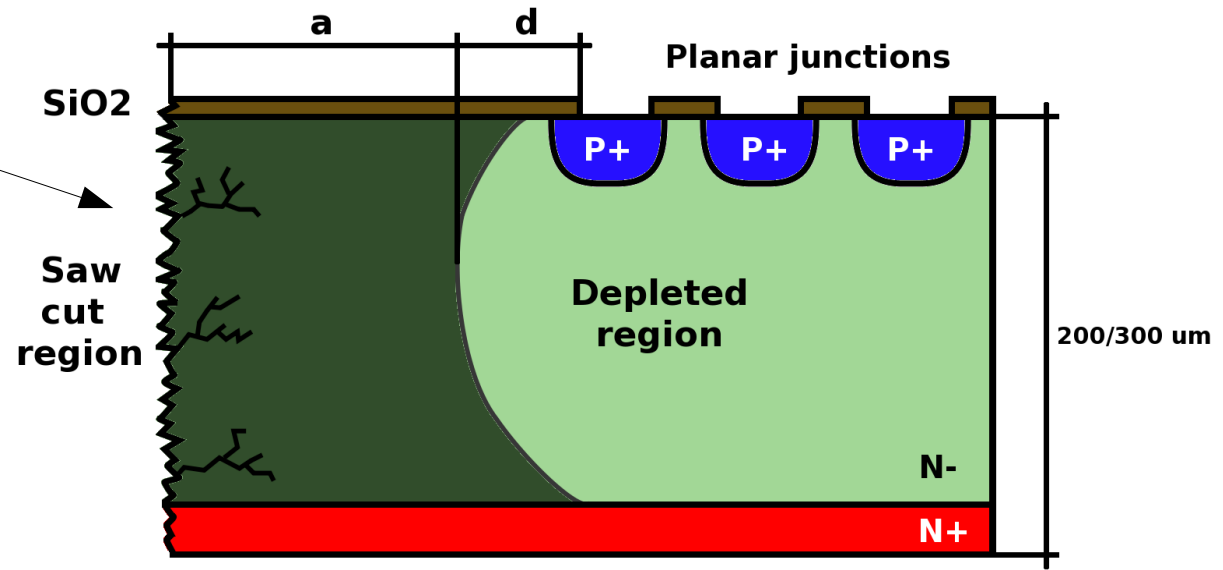
- non-irrad: FDV  $\sim 40$  V, saturated  $> 40$  V  
operated at 150 V bias voltage in test beam
- shown are “in-pixel” efficiency of non-irradiated FE-I4 samples
- p-stop common on Poly Silicon shows best efficiency map
- slight inefficiency beneath the bias rail



Bias voltage dependence of collected charges  
Note: independent charge calibration for non-irradiated and irradiated samples.

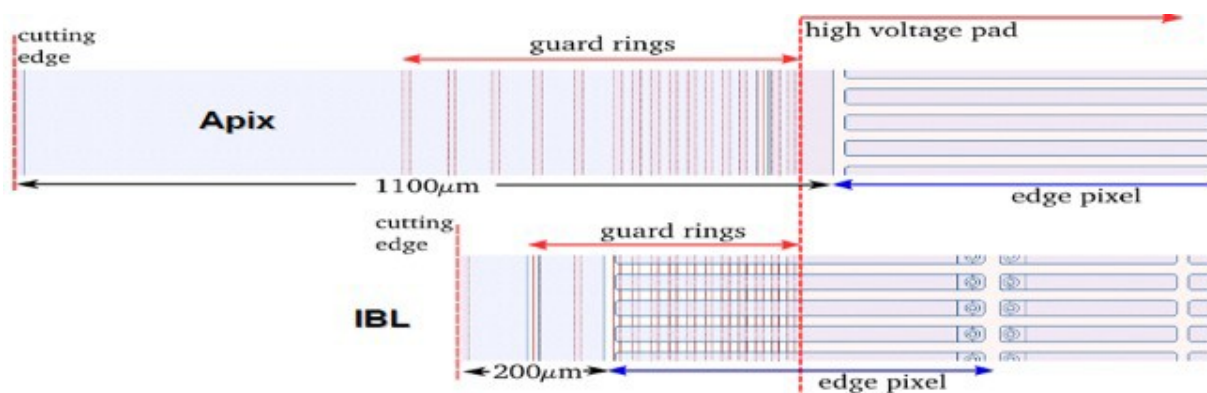
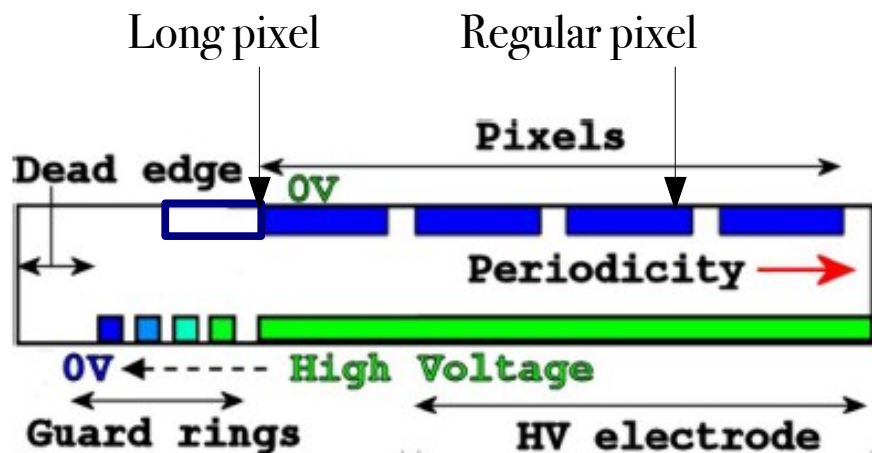
- 4 FE-I4 samples also investigated after irradiation  $2 \cdot 10^{15} n_{eq} \text{ cm}^2$  (FE-I4)
- 2x PolySi-common p-stop: KEK4,5  
PolySi-individual p-stop: KEK3  
PTLA-individual p-stop: KEK6

Dead edge is an inactive area whose purpose is to protect the cut area (full of generation centers) from high electric field



- “It is not possible to obtain the full geometrical coverage in  $z$  as the Pixel detector does, where modules are tilted in  $z$  and are partially overlapped, because there is not enough space. However the gap between modules is minimized using a sensor design with active or slim edges.” IBL TDR

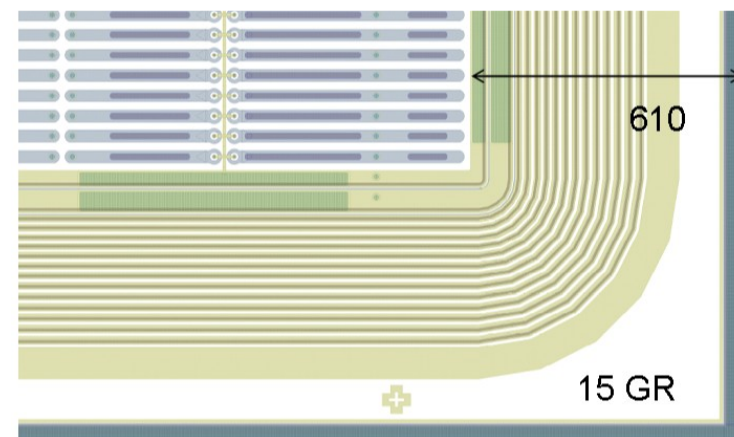
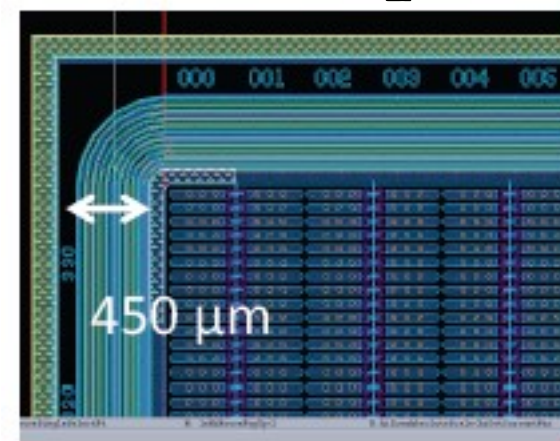
## SLIM EDGES



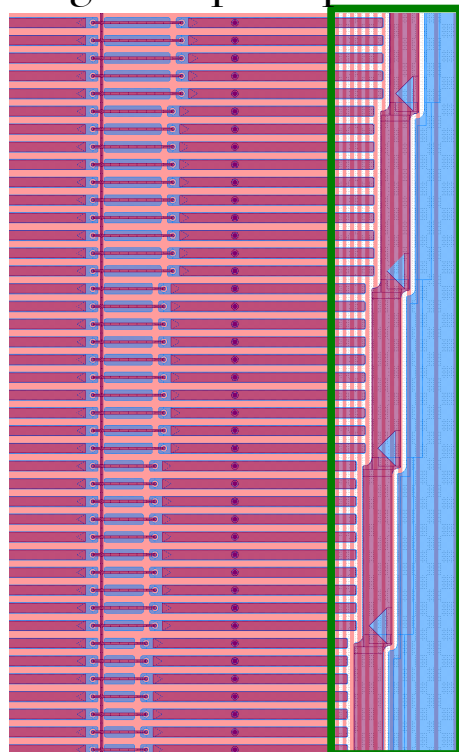
Longer pixel “under the guard-ring”



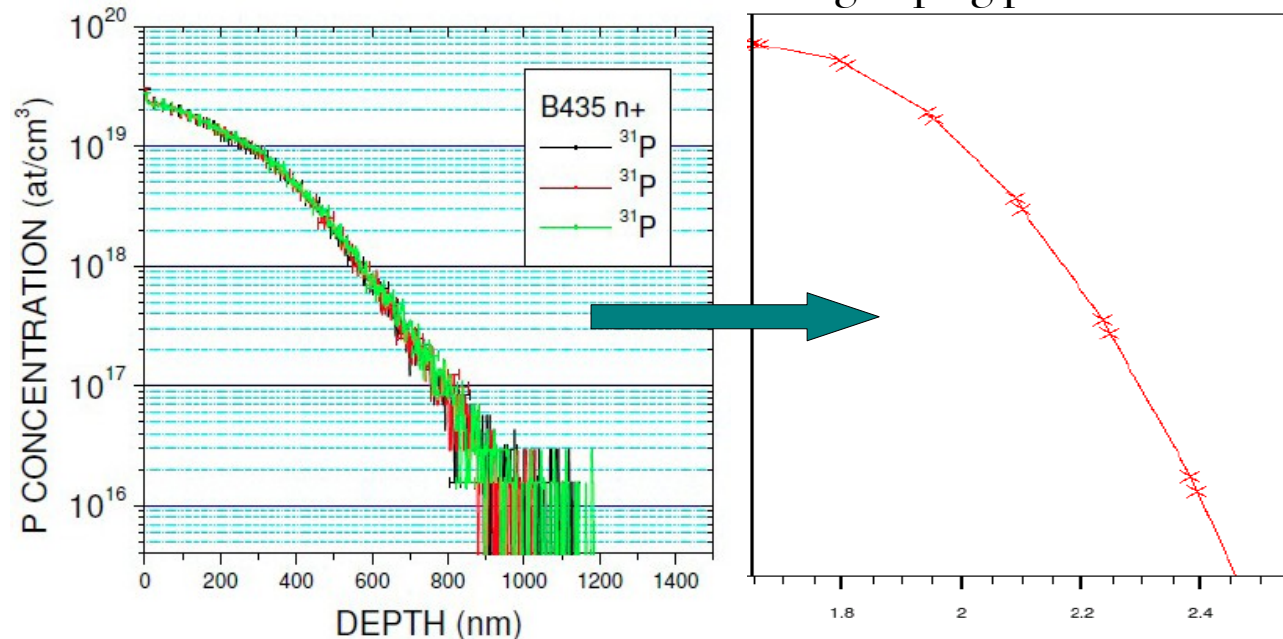
n-in-p



Design: “stepwise pixels”

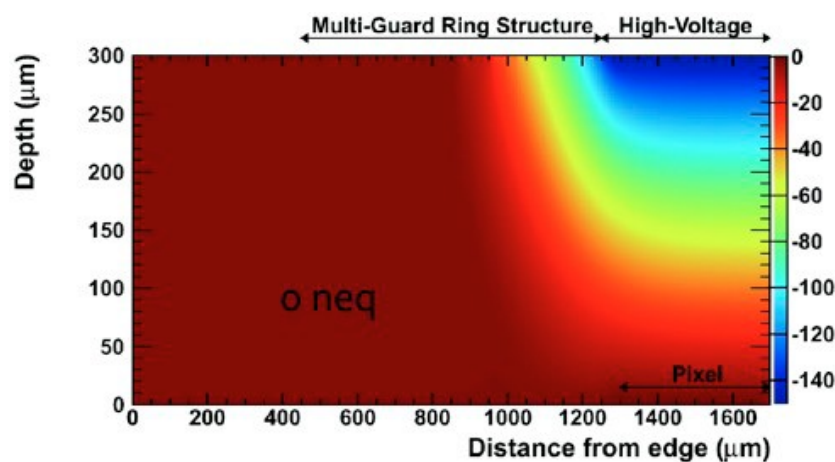


SIMS measurements: determining doping profiles

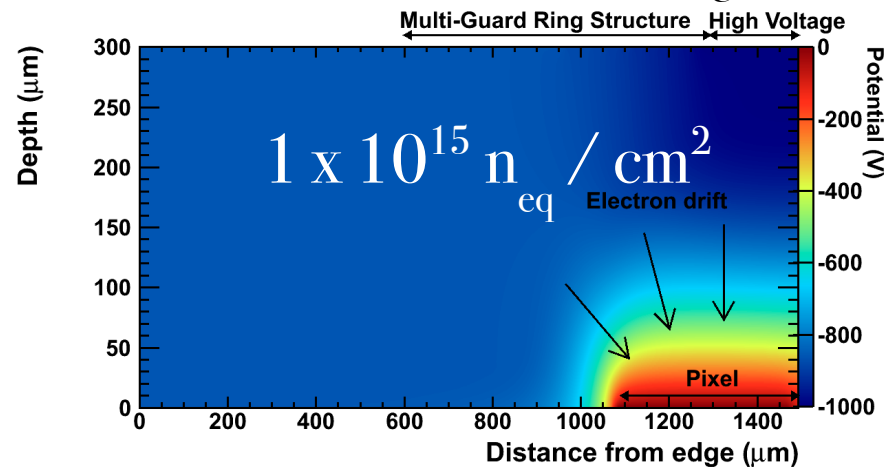


=

Potential before irradiation for a slim edge structure



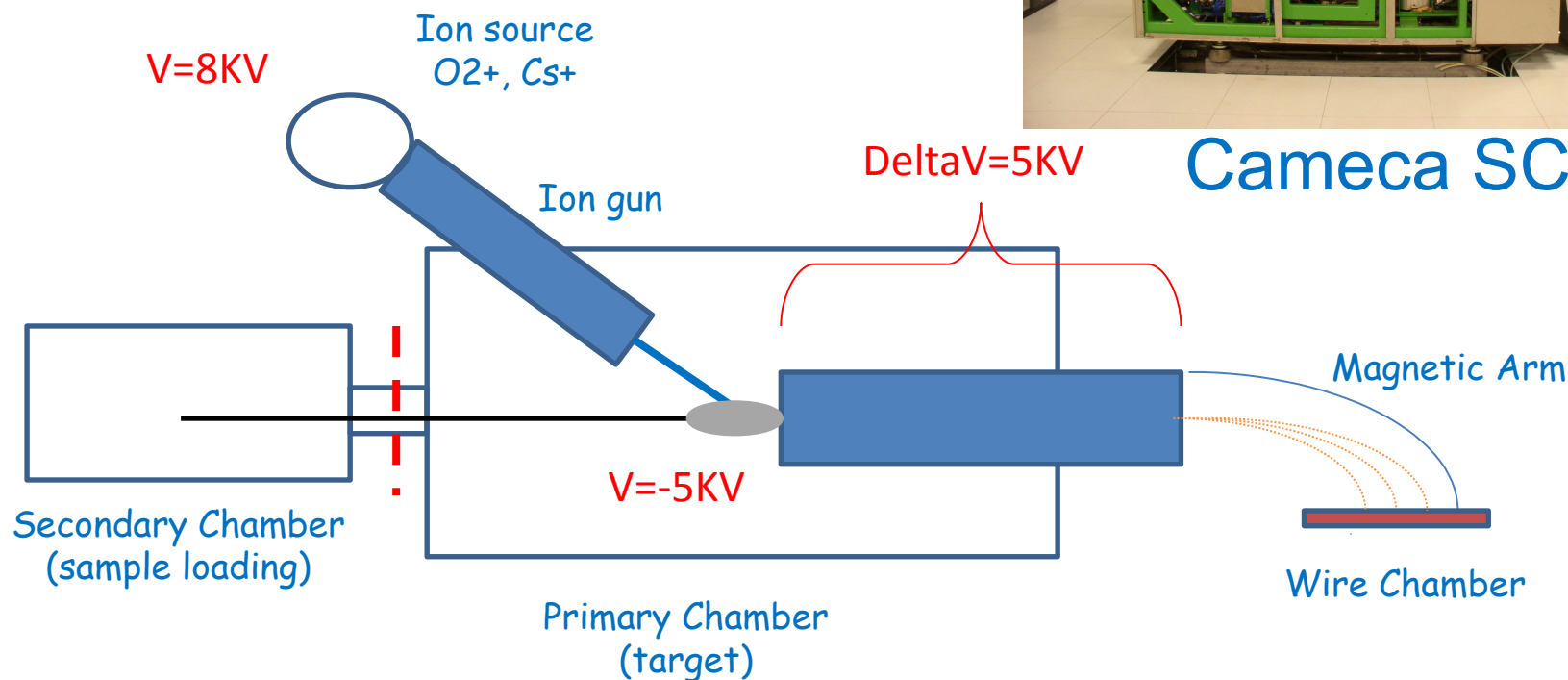
Potential after irradiation for a slim edge structure



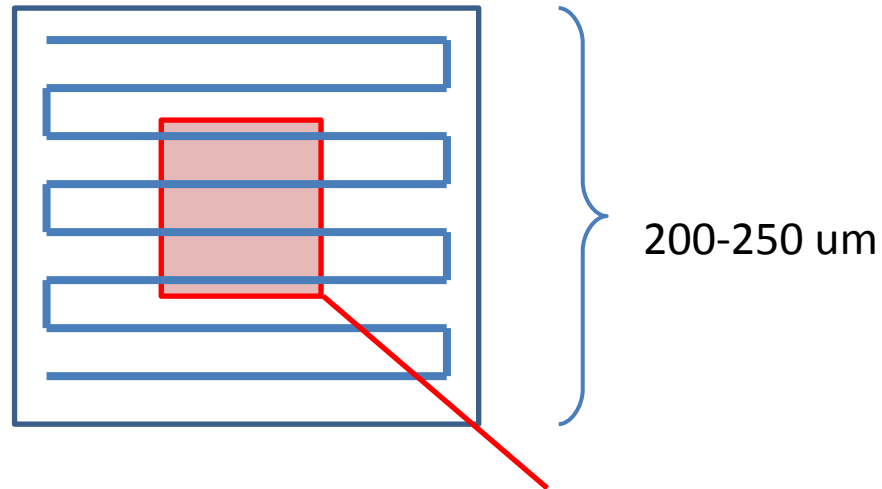
- SIMS: Secondary Ion Mass Spectroscopy



Cameca SC-Ultra



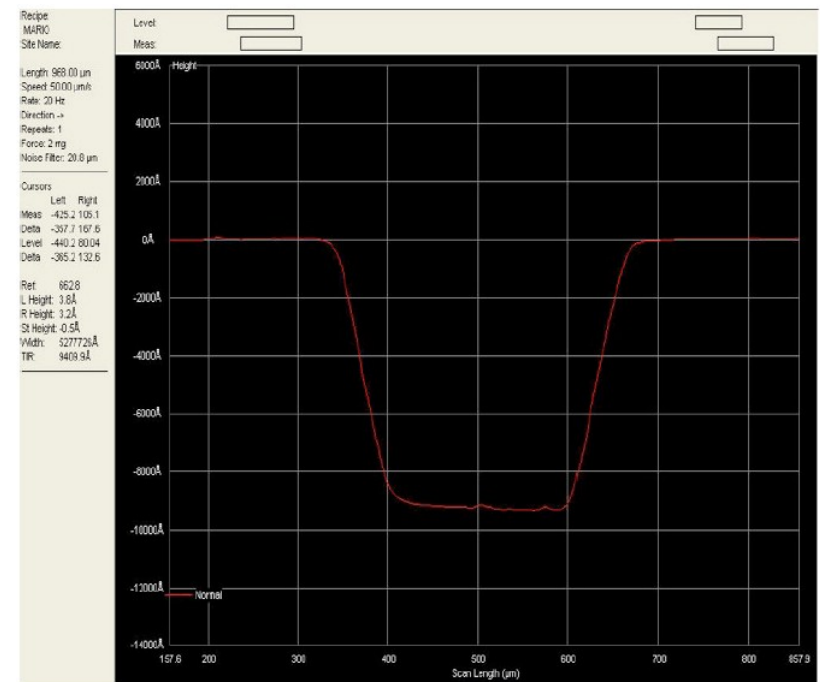
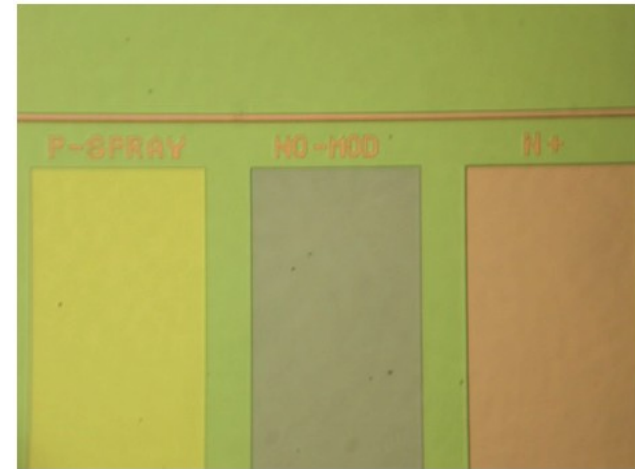
- An ion beam is scanning (and excavating the sample)



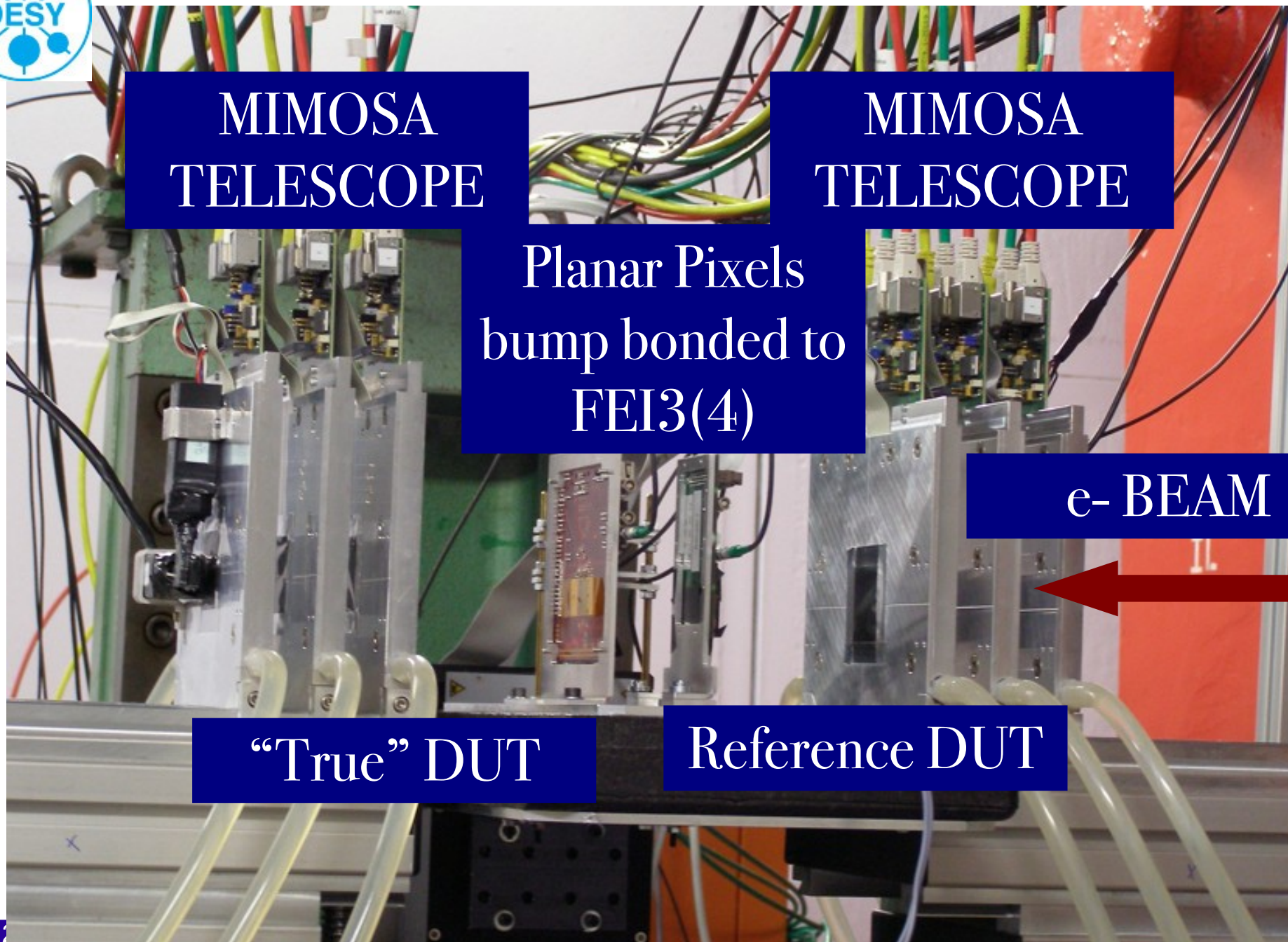
Restricted region analyzed  
(to avoid scattering from walls)



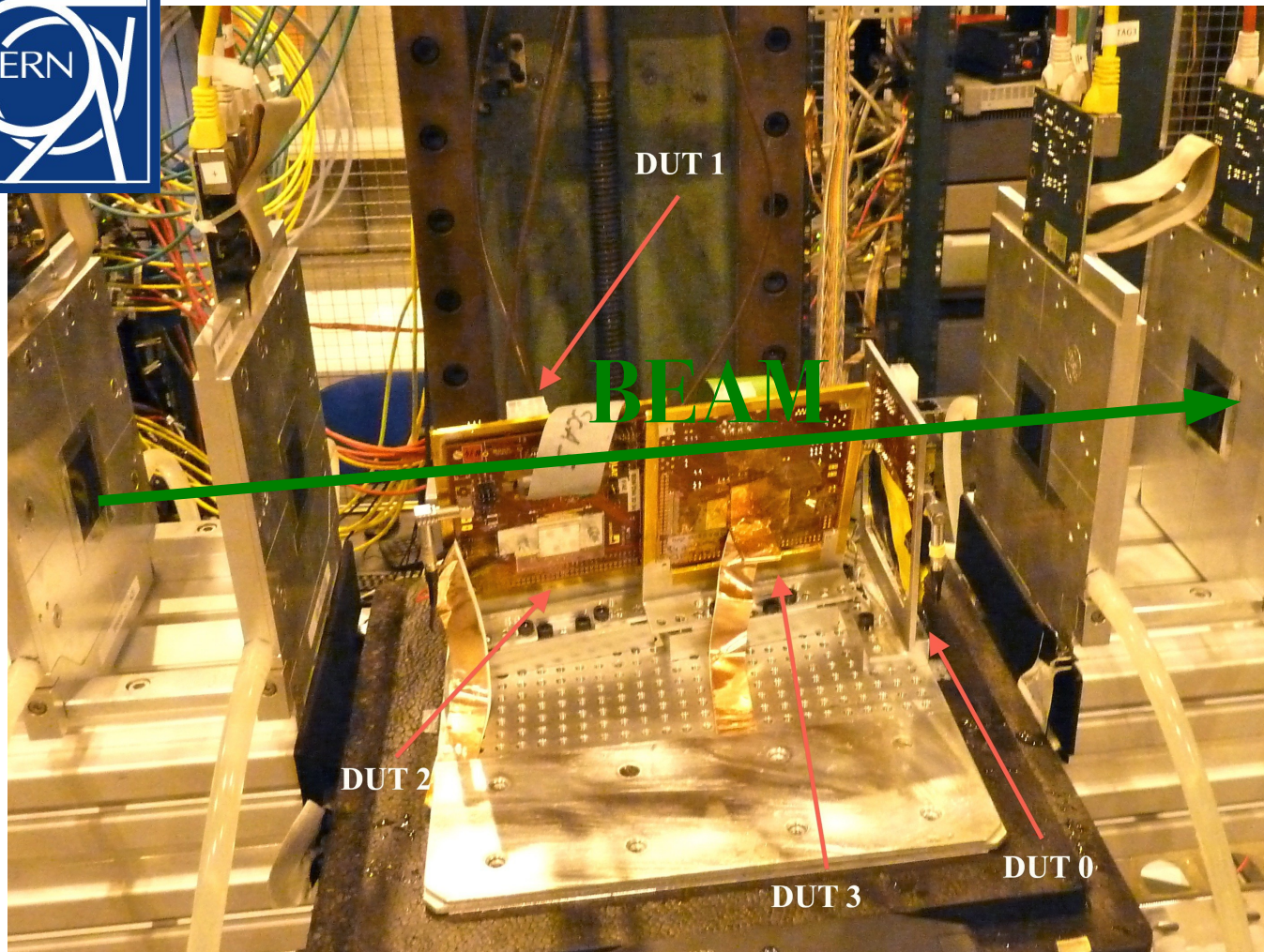
Measured with AFM



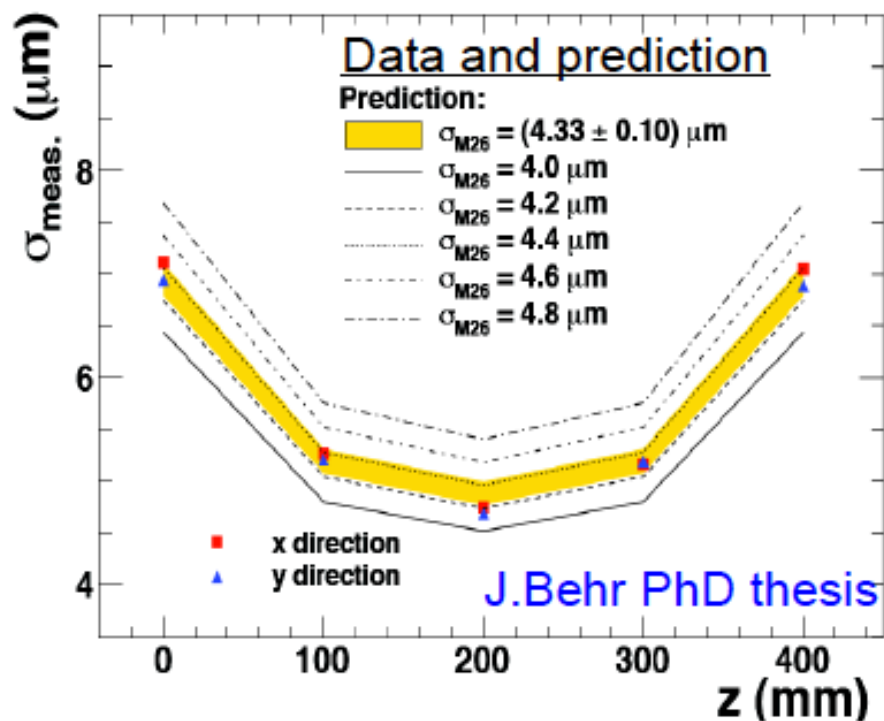
# Intermezzo: test beams



September: CERN SPS (H6B), high-eta DUT setup

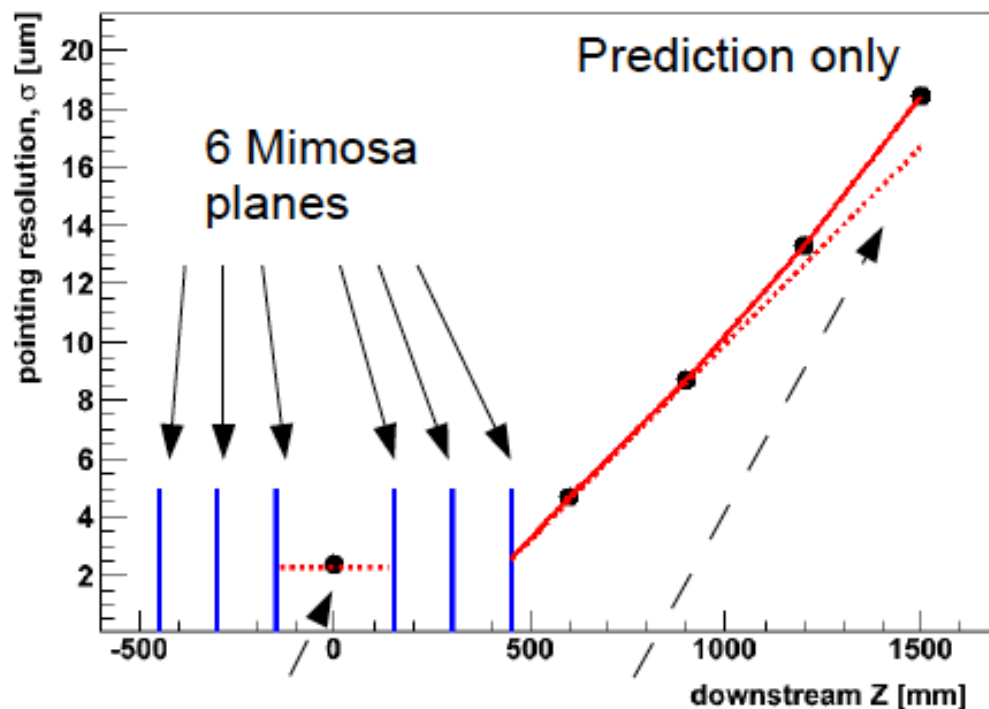


## Pointing resolution in between the planes



$$\sigma_{\text{meas}}^2 = \sigma_{M26}^2 + \sigma_{\text{pointing-resolution}}^2$$

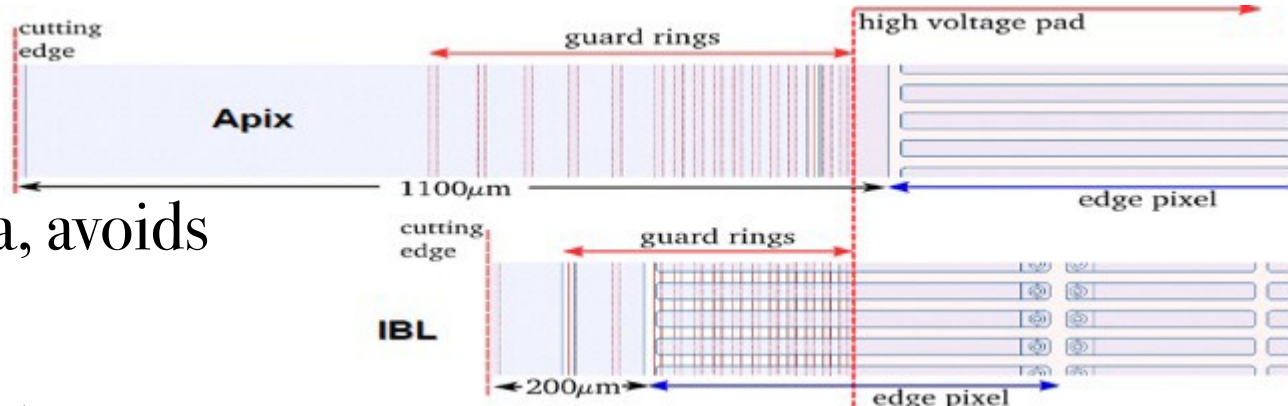
## Track extrapolation accuracy far behind the telescope planes



A DUT within the telescope arms  
 $\sigma \sim 2 \mu\text{m}$

A DUT behind the telescope still can get a very reasonable track pointing resolution  
 $\sigma < 20 \mu\text{m}$

# Slim edge



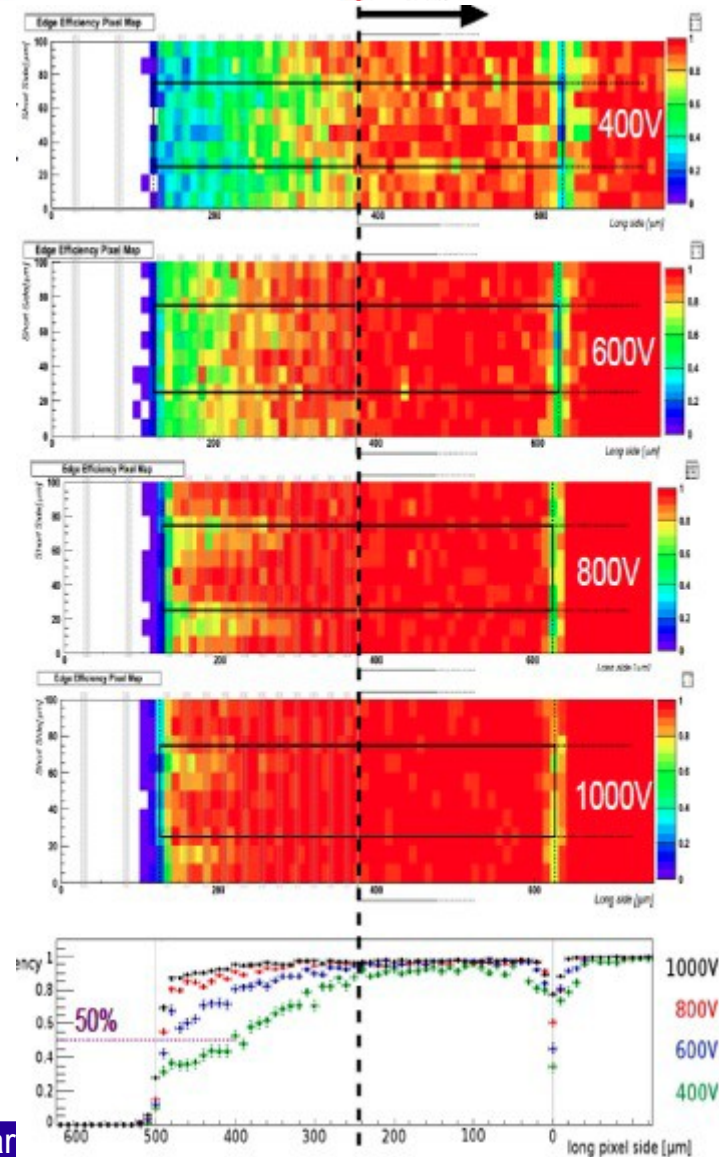
➤ **Goal:** minimize inactive area, avoids shingling along beam axis

➔ **Method:** CiS n<sup>+</sup>-in-in with slim edges, 250 μm thick irradiated to  $4 \cdot 10^{15} \text{ n}_{\text{eq}} \text{ cm}^{-2}$ , data from pion test beam @ CERN

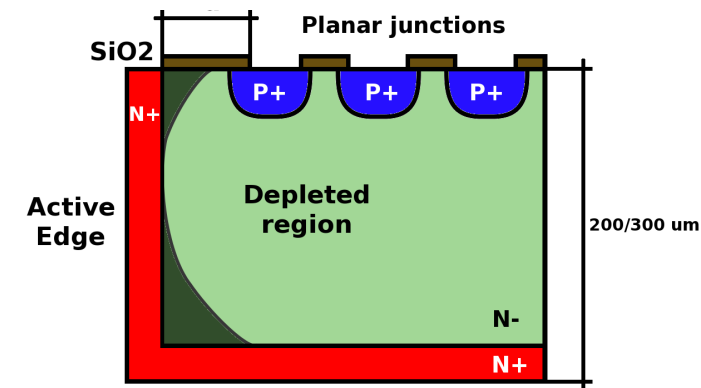
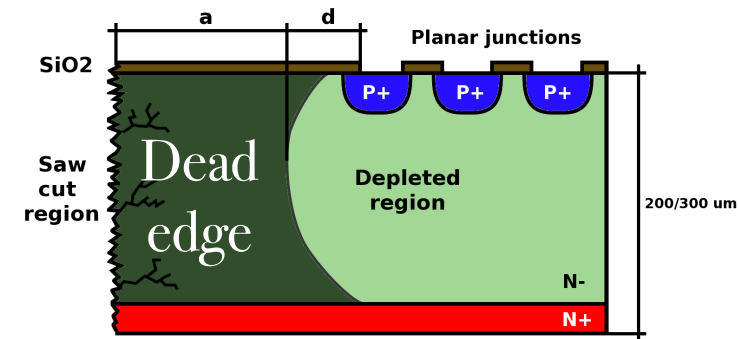
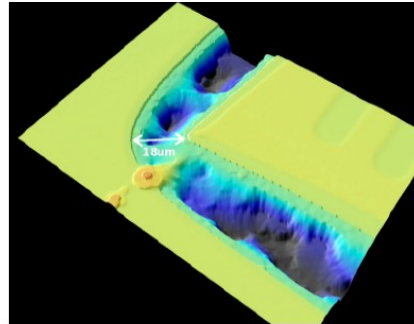
✓ **Result:** significant part of edge pixel sensitive

✓ depends on HV and thickness, inactive edge reduced down to  $\sim 200 \mu\text{m}$

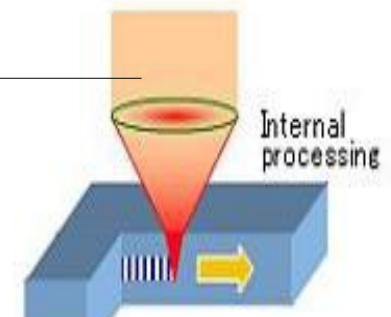
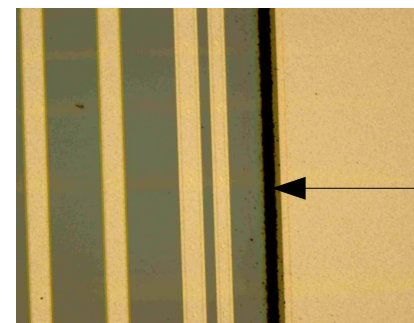
■ design chosen for the planar IBL sensor



- Another approach to **reduce dead area**
- Several ways to do that
- **Drie-etching approaches**
  - ✓ CNM/IFAE
  - ✓ FBK/LPNHE
  - ✓ VTT/Munich
  - Easy to get thin wafers → inner layers?
- **Scribe + cleave + edge – passivation**
  - ✓ UCSC
  - ✓ Dortmund
- Post-processing → outer layers?

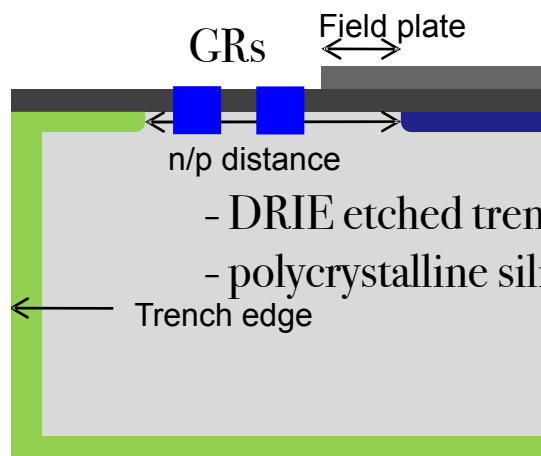


Stealth Dicing

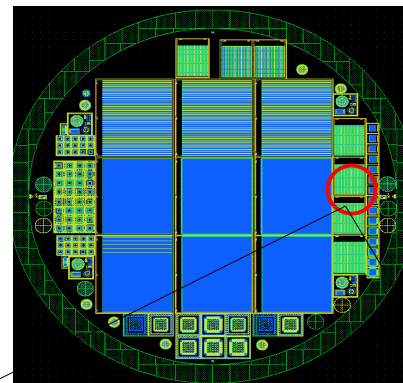


M. Boscardin, A. Baglioni, G. Giacomini, N. Zorzi, E. Vianello, C. Piemonte, M. Povoli, G.F. Dalla Betta

Design – **almost done!**



- DRIE etched trench with p+ doping
- polycrystalline silicon trench filling



On 4 inch wafer:

- 9 FEI4
- 7 FEI3
- Test structures (diodes, ...)

Trench definition and etching

- Aspect Ratio **1/20**
- Deep etching (**200-230  $\mu\text{m}$** )

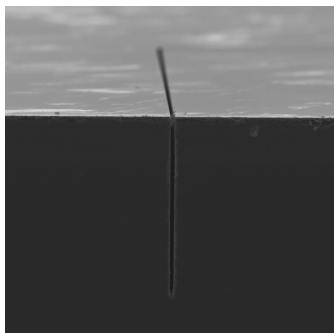
Trench filling

- Trench **width 8-12  $\mu\text{m}$**

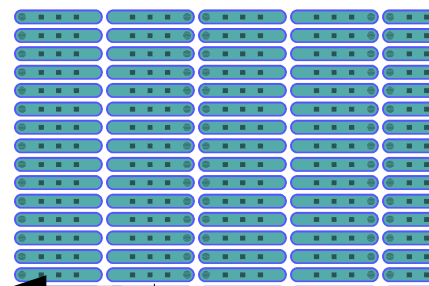
Further trench optimization

Trying to reduce trench  
to **less than 10  $\mu\text{m}$**   
→ **Easier to fill the trench**

4.5  $\mu\text{m}$  wide  
220  $\mu\text{m}$  deep

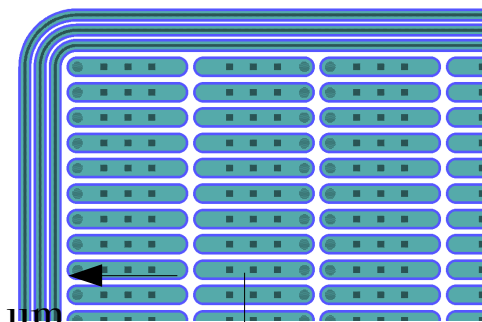


Narrow gap – no GRs



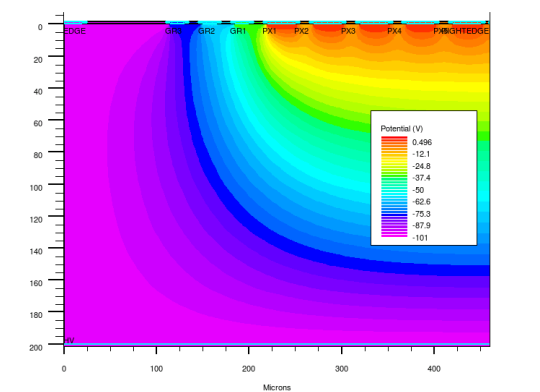
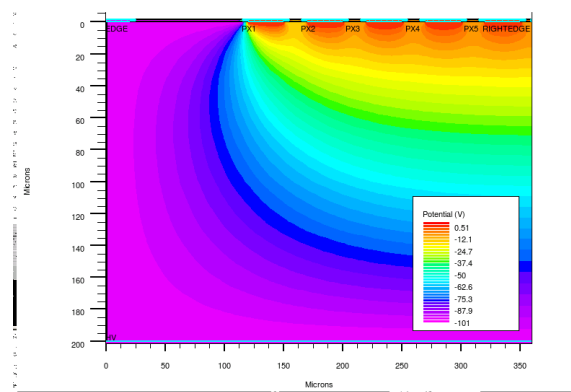
100  $\mu\text{m}$

Wide gap – 3 GRs



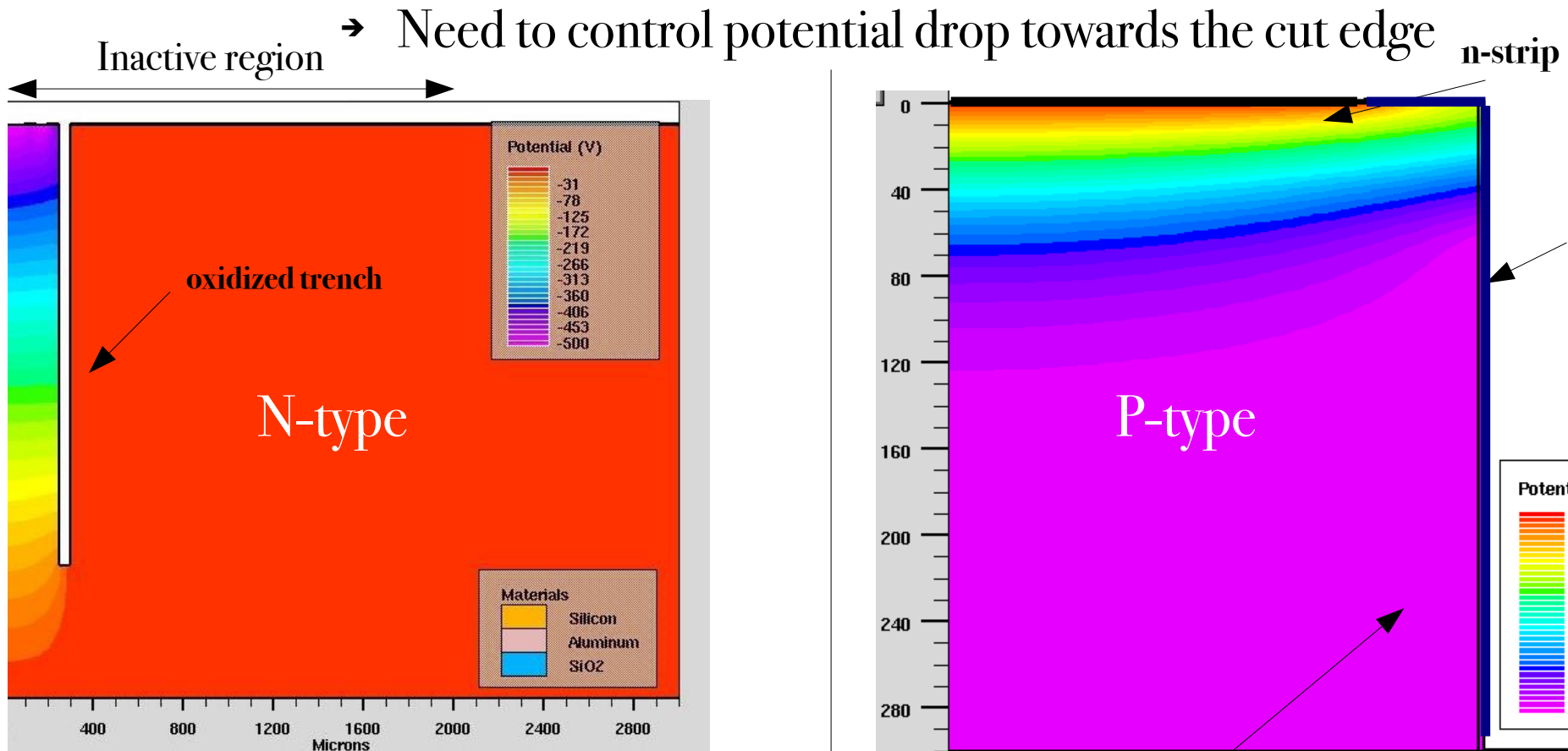
200  $\mu\text{m}$

Potential maps @ 100 V



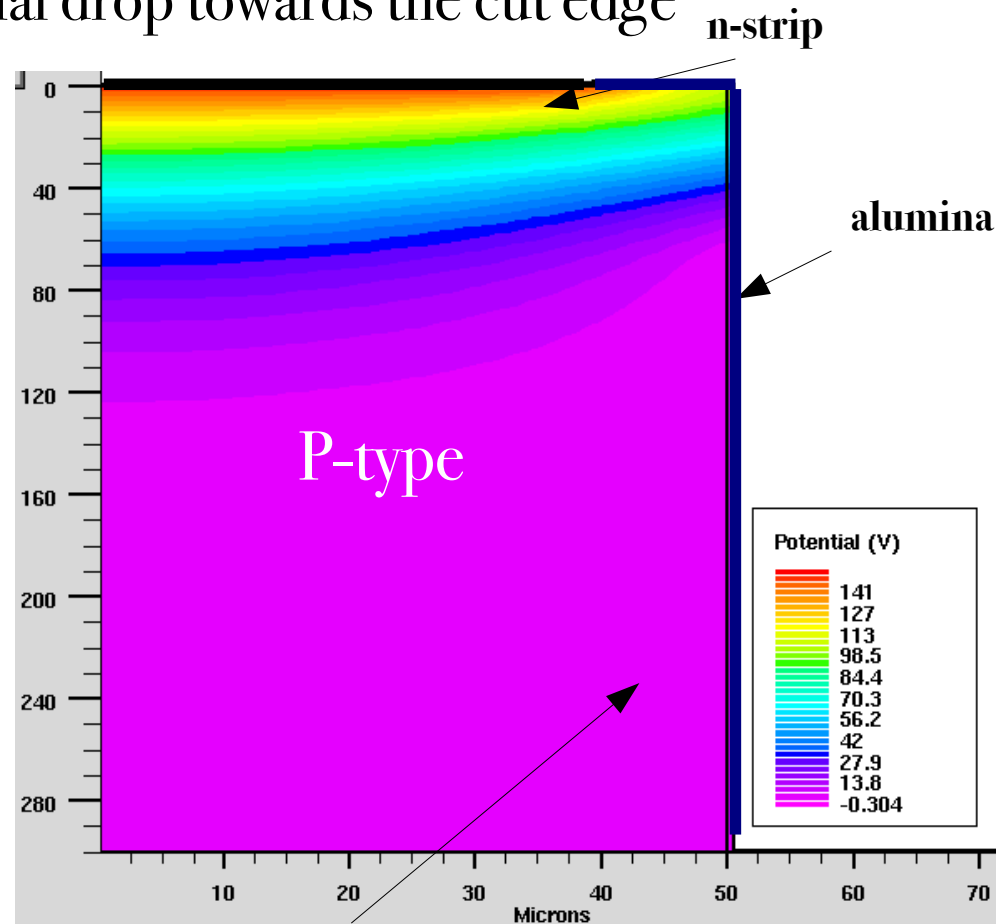
- 1) Final layout: by this week
- 2) Masks ready by mid-February
- 3) Then 4 months for processing
- 4) Late June: start to test in lab first devices
- 5) July: irradiations
- 6) August: bump bonding
- 7) Late August/September: test on irradiated devices
- 8) October/November: beam test!

# Passivated trench



A passivated trench with a thermally grown oxide (**positive** charge density  $10^{11} \text{ cm}^{-2}$ ) trench will lead to:

- ✓ control potential drop toward the cut edge,
- ✓ protection from saw cut edge.
- Scribe + nitride/oxide deposit approach too



Negative charge ( $-1\text{E}11 \text{ cm}^{-2}$ )

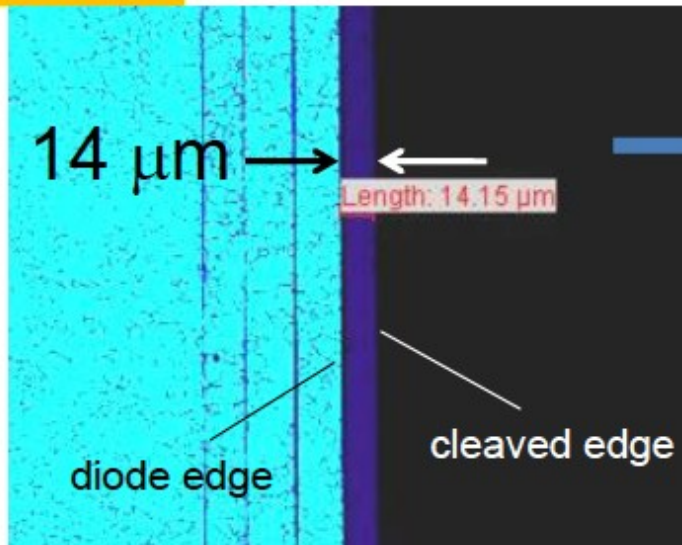
Alumina deposition by ALD

- ✓ Partially controlled potential drop towards the cut edge
- The more charge, the better

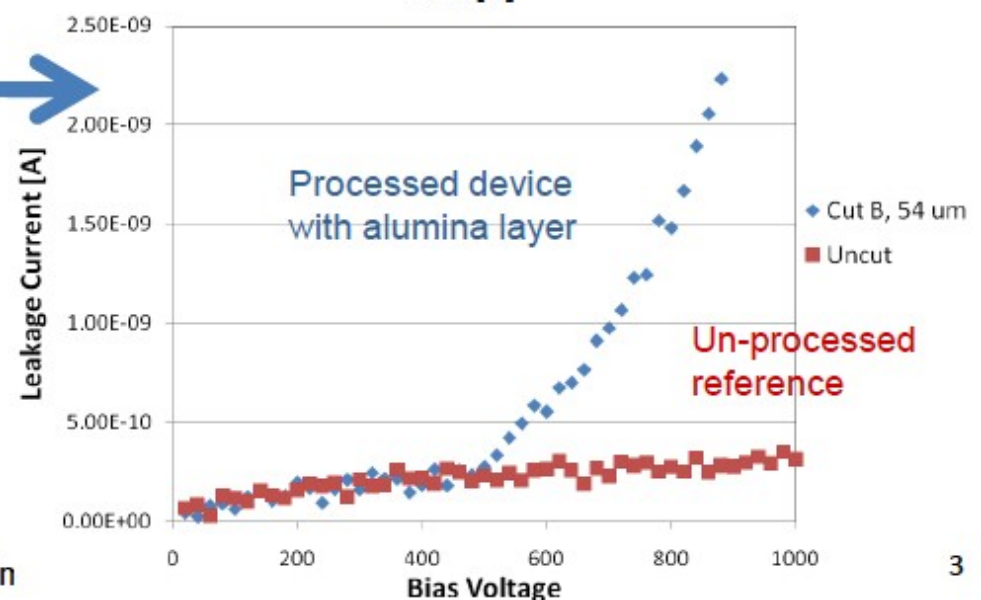
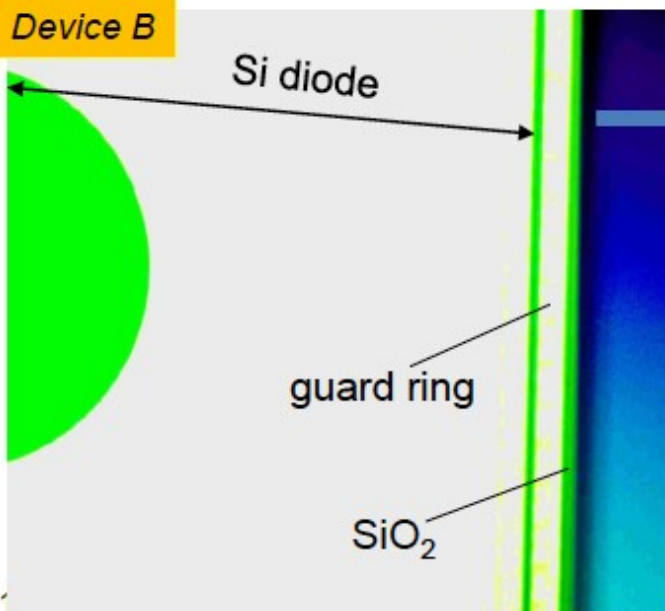
# P-type passivated trench

## Examples of Processed Devices

Device A



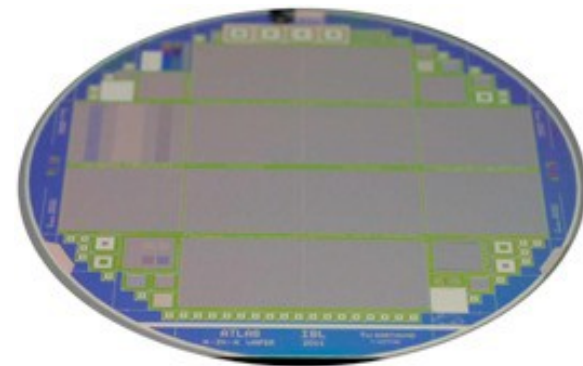
Device B



# CONCLUSIONS

- A major upgrade of LHC will turn it into a High Luminosity machine
- Foreseen instant and integrated luminosities translate into high occupancies and irradiation fluences for the future ATLAS tracker
- Planar Pixel Sensors Upgrade is investigating the planar technology option
- The PPS group proved radiation hardness of n-&p-type bulk material for a fluence of  $5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$  and showed promising results for  $O(10^{16} \text{ n}_{\text{eq}}/\text{cm}^2)$
- Dead-area reduction is addressed by means of slim/active edge
- New designs, for both n- & p-type material, including thin bulk, are being studied
- More beamtests will help in realizing the future ATLAS pixel system

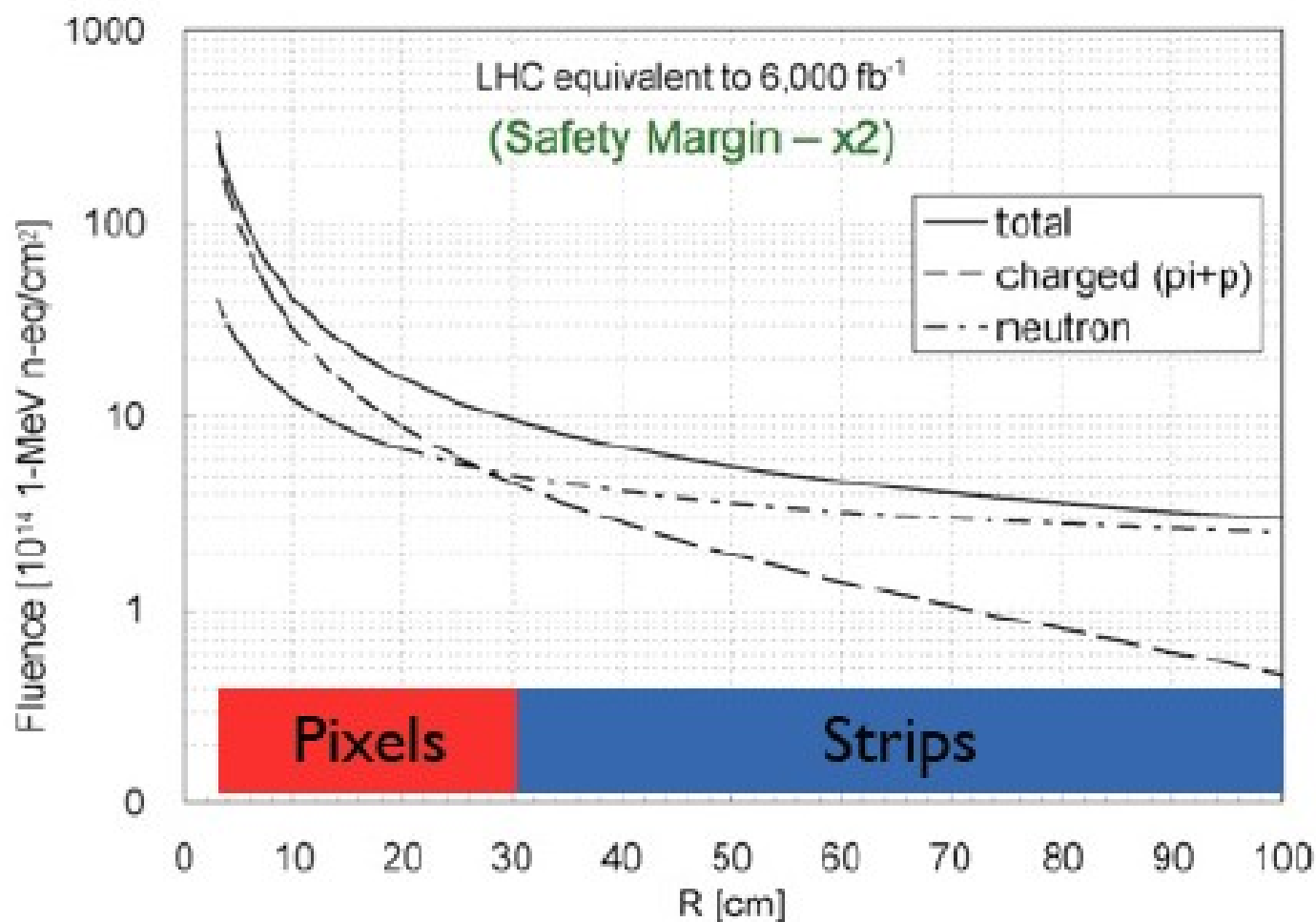
- CERN: D. Dobos, C. Gallrapp, B. Di Girolamo, D. Muenstermann, H. Pernegger, S. Roe
- AS CR, Prague (Czech Rep.) : V. Vrba, P. Sicho, J. Popule, M. Tomasek, L. Tomasek, J. Stastny, M. Marcisovsky, M. Havranek, J. Bohm, Z. Janoska, M. Hejtmanek
- LAL Orsay (France): M. Benoit, N. Dinu, D. Fournier, J. Idarraga, A. Lounis
- LPNHE / Paris VI (France): M. Bomben, G. Calderini, J. Chauveau, G. Marchiori, P. Schwemling
- University of Bonn (Germany): M. Barbero, F. Hügging, H. Krüger, N. Wermes
- HU Berlin (Germany): H. Lacker
- DESY (Germany): C. Hengler, I. M. Gregor, U. Husemann, V. Libov, I. Rubinsky
- TU Dortmund (Germany): S. Altenheiner, C. Gößling, J. Jentzsch, T. Lapsien, R. Klingenberg, A. Rummler, G. Troska, T. Wittig, R. Wunstorf
- University of Goettingen (Germany): J. Grosse-Knetter, M. George, A. Quadt, J. Weingarten
- MPP und HLL Munich (Germany): L. Andricek, M. Beimforde, A. Macchiolo, H.-G. Moser, R. Nisius, R. Richter, P. Weigell
- Università degli Studi di Udine – INFN (Italy): D. Cauz, M. Cobal, C. del Papa, D. Esseni, M. P. Giordani, P. Palestri, G. Pauletta, L. Selmi
- KEK (Japan): Y. Unno, S. Terada, Y. Ikegami, Y. Takubo
- IFAE-CNM, Barcelona (Spain): M. Cavalli, S. Grinstein, Korolkov, M. Lozano, C. Padilla, G. Pellegrini, S. Tsiskaridze
- University of Liverpool (UK): T. Affolder, P. Allport, G. Casse, T. Greenshaw, I. Tsurin
- UC Berkeley/LBNL (USA): M. Battaglia, T. Kim, S. Zalusky
- UNM, Albuquerque (USA): I. Gorelov, M. Hoferkamp, S. Seidel, K. Toms
- UCSC, Santa Cruz (USA): V. Fadeyev, A. Grillo, J. Nielsen, H. Sadrozinski, B. Schumm, A. Seiden



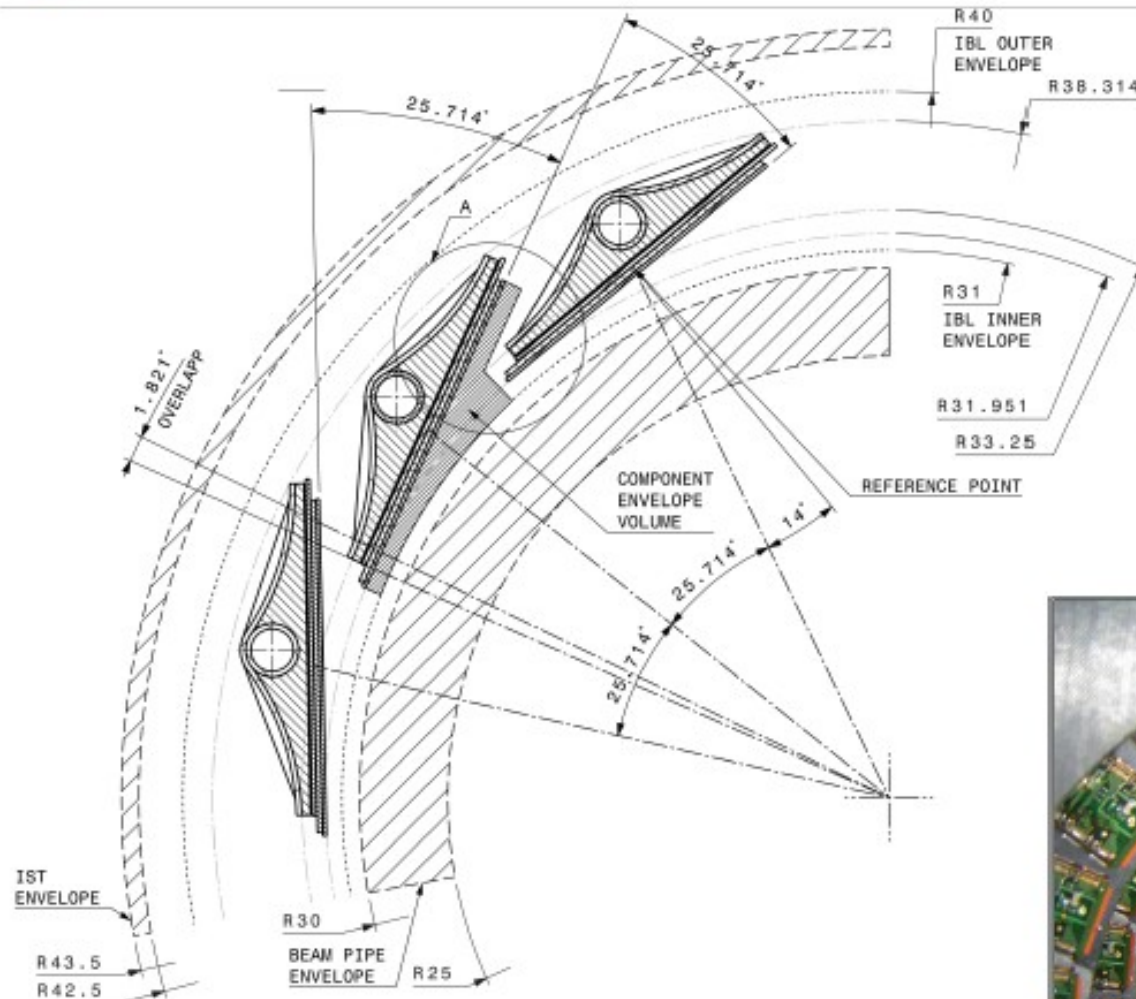
# BACKUP

# LHC main figures

Circumference (km)	26.7	100-150m underground
Number of <b>superconducting twin-bore Dipoles</b>	1232	Cable Nb-Ti, cold mass 37million kg
Length of Dipole (m)	14.3	
Dipole Field Strength (Tesla)	8.4	Results from the high beam energy needed
Operating Temperature (K) ( <b>cryogenics system</b> )	1.9	Superconducting magnets needed for the high magnetic field Super-fluid helium
Current in dipole sc coils (A)	13000	Results from the high magnetic field 1ppm resolution
Beam Intensity (A)	0.5	$2.2 \cdot 10^{-6}$ loss causes quench
Beam Stored Energy (MJoules)	362	Results from high beam energy and high beam current 1MJ melts 1.5kg Cu
Magnet Stored Energy (MJoules)/octant	1100	Results from the high magnetic field
Sector Powering Circuit	8	1612 different electrical circuits



- fluences for the innermost pixel layer:  $1.5 \times 10^{16} \text{ n}_{\text{eq}}/\text{cm}^2 (3 \text{ ab}^{-1})$
- **Radiation hard components**



## Beam-pipe reduction:

- Inner R: 29 → 25 mm

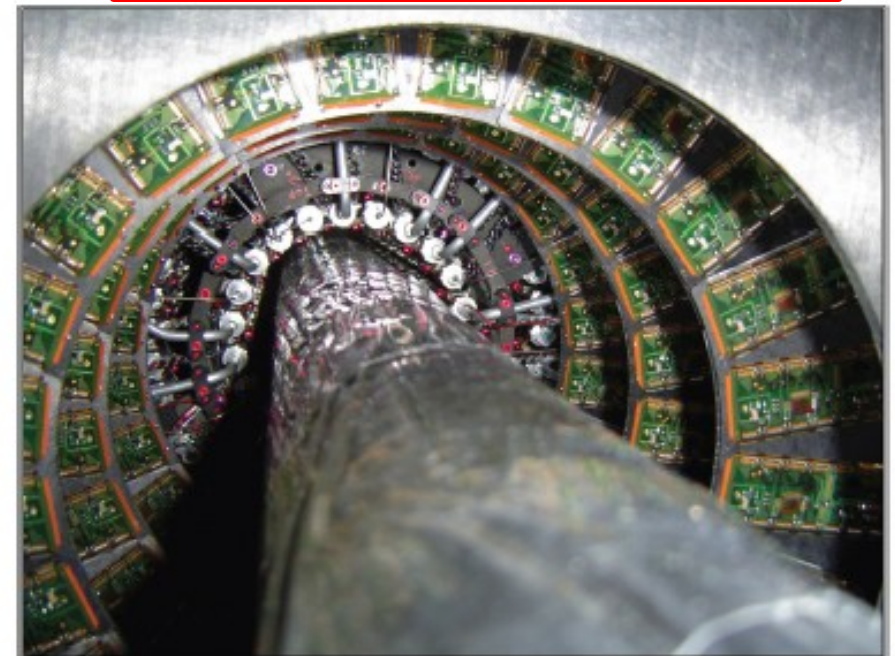
## Very tight clearance:

- "Hermetic" to straight tracks in  $\Phi$  ( $1.8^\circ$  overlap)
- No overlap in Z: minimize gap between sensor active area.
- Coverage in  $\eta$  ( $2\sigma$ -vertex spread): 2.6

## Material budget:

- Stave, el.serv. Module: 1.16 %  $X_0$
- IBL Sup.Tube (IST): 0.28 %  $X_0$

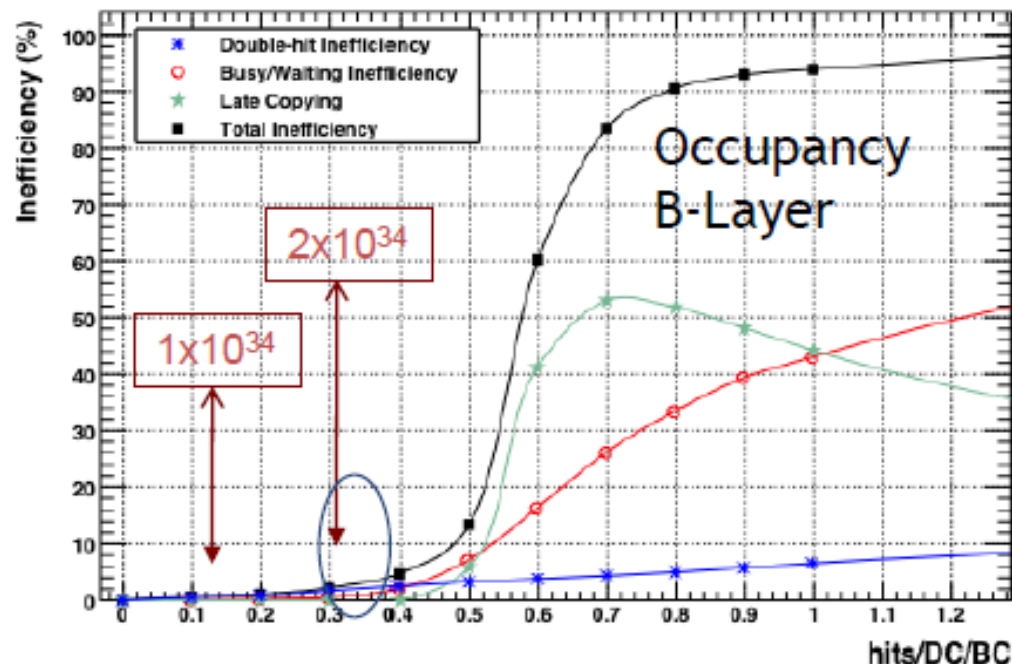
- Beam-pipe (BP) extracted by cutting the flange on one side and sliding (guiding tube inside).
- IBL Support Tube (IST) inserted.
- IBL with smaller BP inserted in the IST



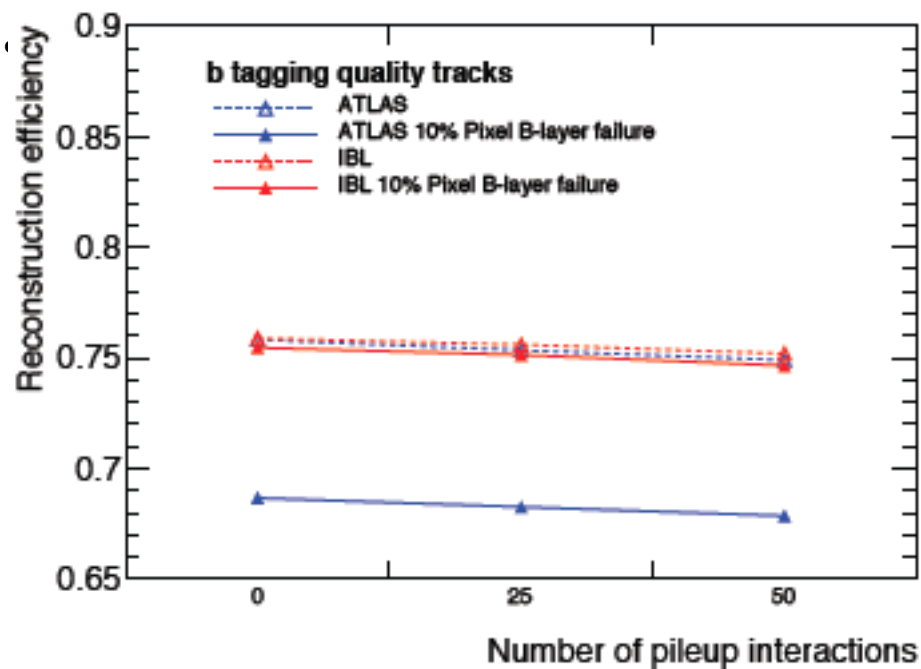
# Insertable B-Layer: Motivations



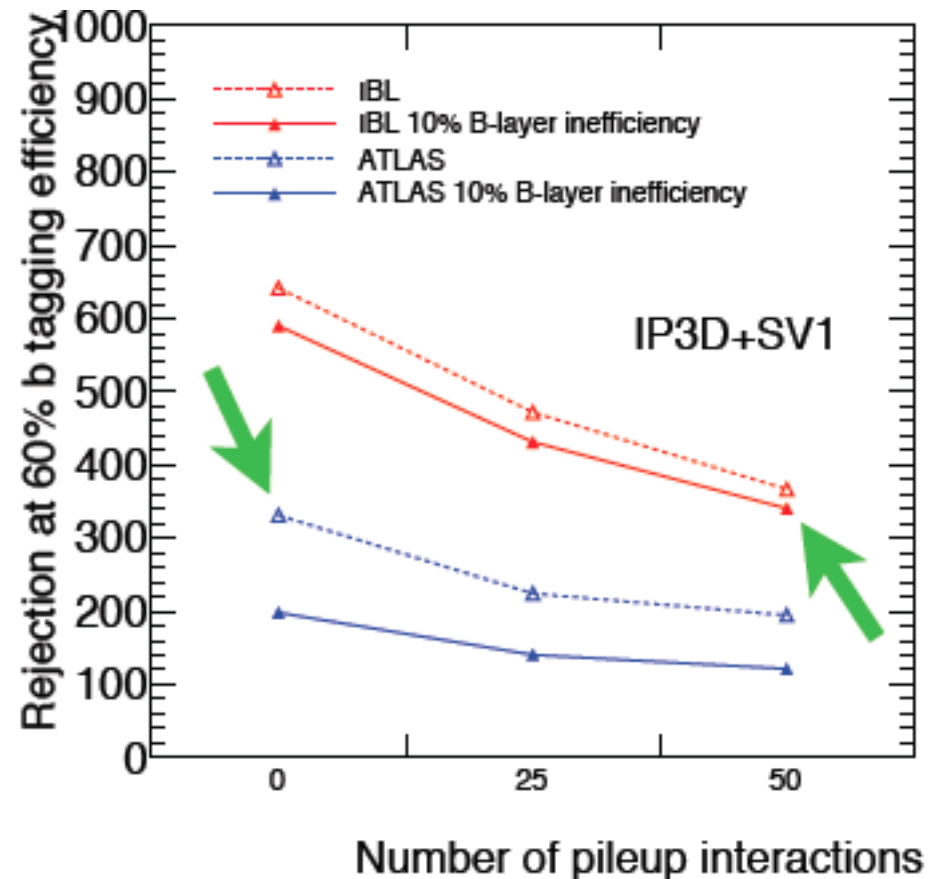
- ✓ Motivations for a 4<sup>th</sup> low radius layer in the Pixel Detector
  - Luminosity pileup
    - FE-I3 has 5% inefficiency at the B-layer occupancy for  $2.2 \times 10^{34} \text{cm}^{-2}\text{s}^{-1}$
  - IBL improves tracking, vertexing and b-tagging for high pileup and recovers eventual failures in present Pixel detector.
    - Today the B-layer has 3.1% of inefficiency.



- Radiation damage
  - Degradation of the existing B-Layer reduce detector efficiency after 300-400  $\text{fb}^{-1}$ . Not an issue as forecast for 2021 is  $\sim 330 \text{fb}^{-1}$
- It serves also as a technology step towards HL-LHC.
- IBL Installation foreseen in 2013, during LHC first shutdown.



In a scenario with a 10% cluster inefficiency in the actual B-layer, the IBL recovers tracking efficiency and impact resolution

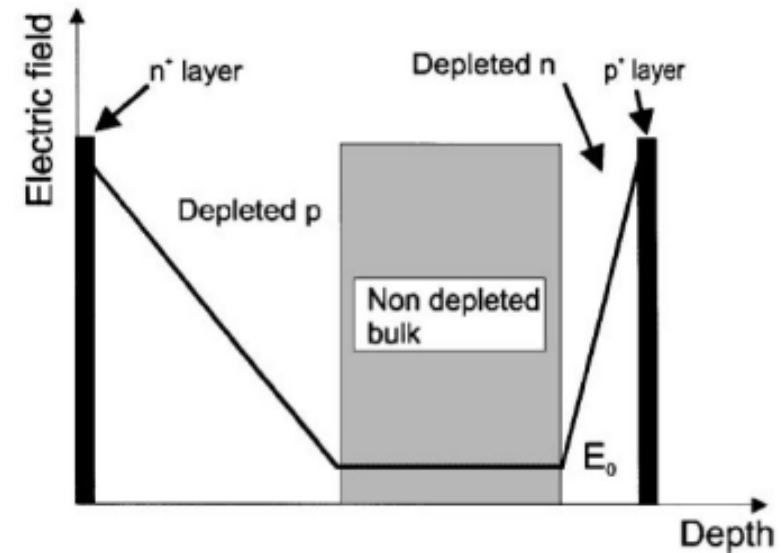


- Only minor effect on b-tagging performances
- Performing better than ATLAS w/o defects and pileup!

N-side read-out can make planar segmented Si detectors suitable for tracking in extreme (SLHC levels:  $1\text{-}2 \times 10^{16} \text{ cm}^{-2}$ ) radiation environments.

Schematic changes  
of Electric field  
after irradiation

Effect of trapping on  
the Charge Collection  
Efficiency (CCE)



$$Q_{tc} \cong Q_0 \exp(-t_c/\tau_{tr}), \quad 1/\tau_{tr} = \beta\Phi.$$

Collecting electrons provide a sensitive advantage with respect to holes due to a much shorter  $t_c$ . P-type detectors are the most natural solution for  $e$  collection on the segmented side.

N-side read out  
to keep lower  $t_c$

## Effect of trapping on the Charge Collection Distance

After heavy irradiation the charge collection distance (CCD) of thin detectors should have a similar (better?) charge collection efficiency (CCE) as thicker ones.

The reverse current is proportional to the depleted volume in irradiated detectors. Do thin sensors offer an advantage in term of reduced reverse current compared to thicker ones (this aspect is particularly important for the inner layer detectors of SLHC, where significant contribution to power consumption is expected from the sensors themselves)?

$$Q_{tc} \cong Q_0 \exp(-t_c/\tau_{tr}), 1/\tau_{tr} = \beta\Phi.$$

$$V_{sat,e} \times \tau_{tr} = \lambda_{av}$$

$$\beta_e = 4.2E-16 \text{ cm}^2/\text{ns}$$

$$\beta_h = 6.1E-16 \text{ cm}^2/\text{ns}$$

G. Kramberger et al.,  
NIMA 476(2002), 645-651.

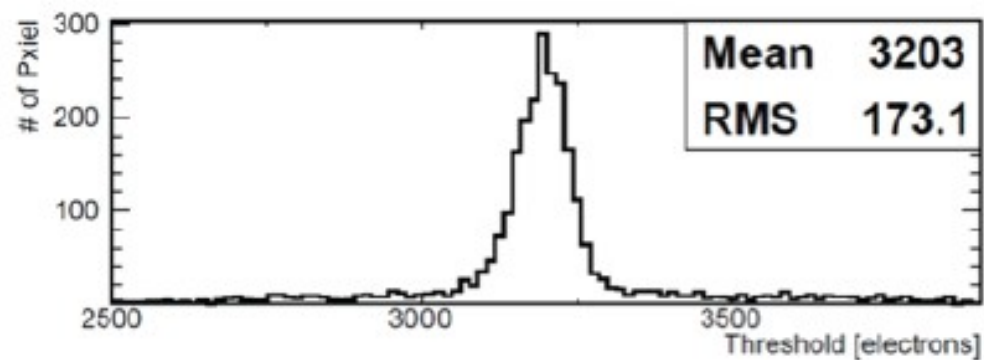
$$\lambda_{Max,n} (\Phi=1e14) \cong 2400\mu\text{m}$$

$$\lambda_{Max,n} (\Phi=1e16) \cong 24\mu\text{m}$$

$$\lambda_{Max,p} (\Phi=1e14) \cong 1600\mu\text{m}$$

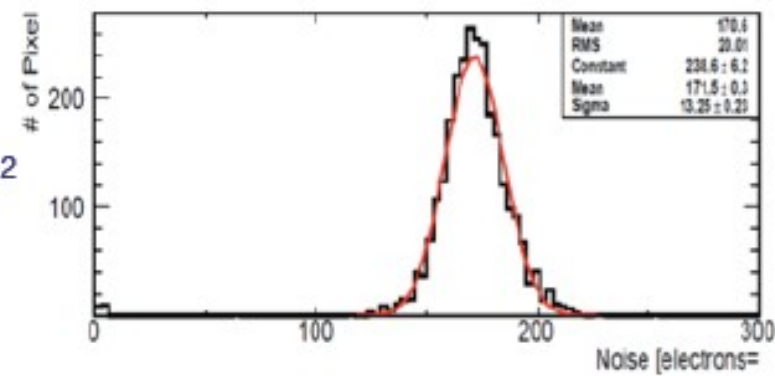
$$\lambda_{Max,p} (\Phi=1e16) \cong 16\mu\text{m}$$

# N-in-p tuning



$5 \cdot 10^{15} \text{ n}_{\text{eq}} \text{cm}^{-2}$

$V_{\text{bias}} = 1 \text{ kV}$



- × CMOS 0.35  $\mu\text{m}$
- × Pixel size:  $18.4 \times 18.4 \mu\text{m}^2$
- × Rolling shutter mode
  - at 80 MHz  $\rightarrow$  112.5  $\mu\text{s}$  per frame
  - no deadtime, continues readout
  - digital (binary) readout
- × In pixel amplification
- × 1 discriminator per column with
  - Offset compensation
  - Correlated Double Sampling
- × Built-in data sparsification
- × Current version of Mimosa26:
  - High resistivity epitaxial
  - Backthinned down to 50  $\mu\text{m}$

